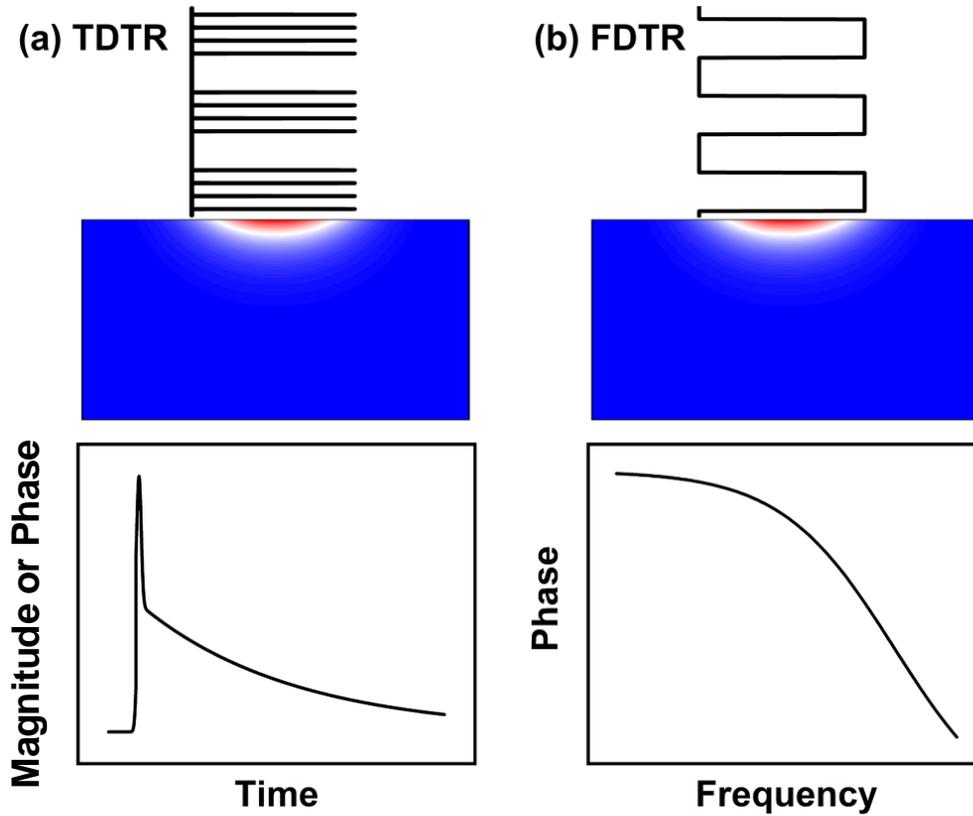


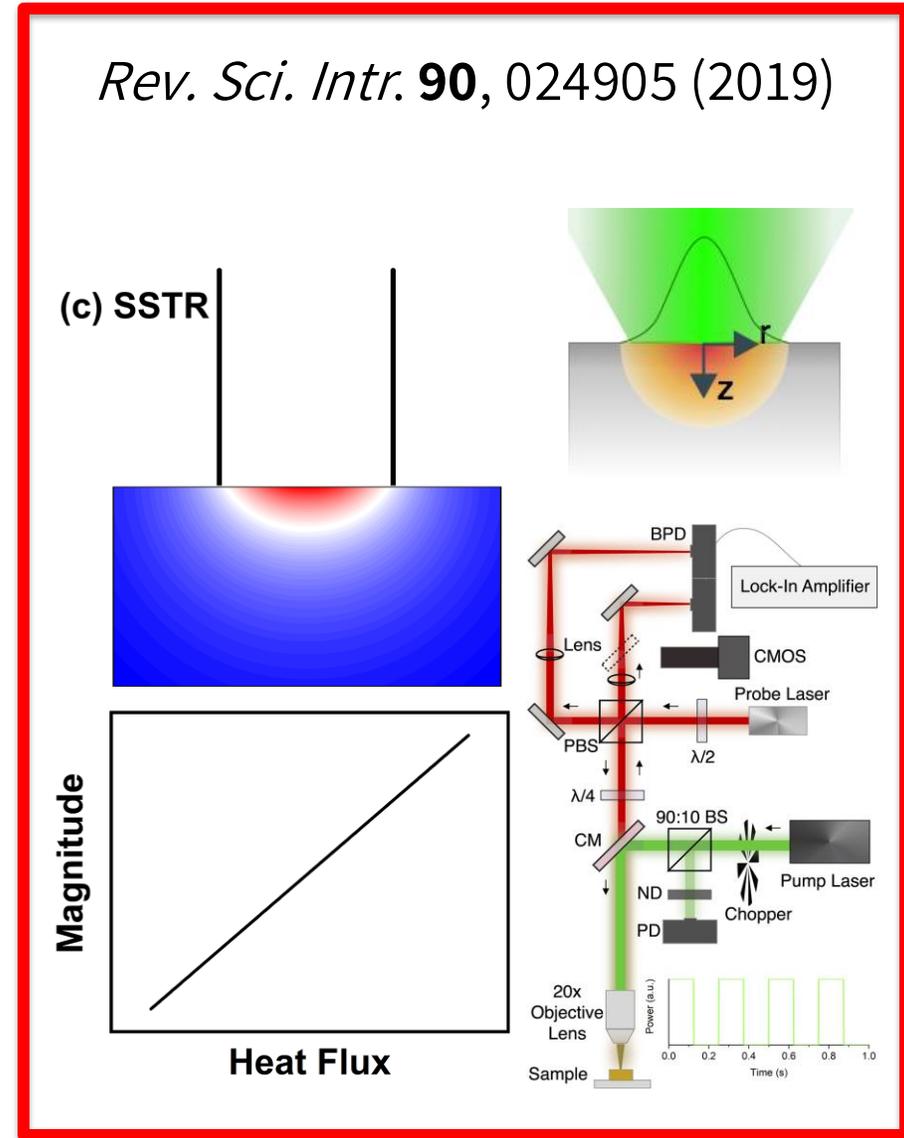
# Steady-State Thermoreflectance: A Practical Guide

Jeffrey L. Braun

Vice President of Strategy and Programs  
Laser Thermal Analysis, Inc.  
937 2<sup>nd</sup> St. SE  
Charlottesville, VA 22902



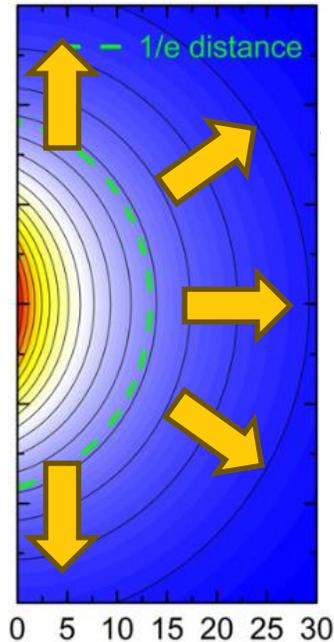
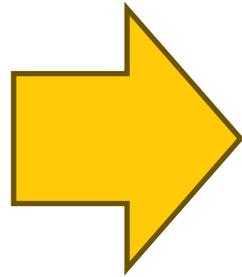
J. Appl. Phys. **126**, 150901 (2019)



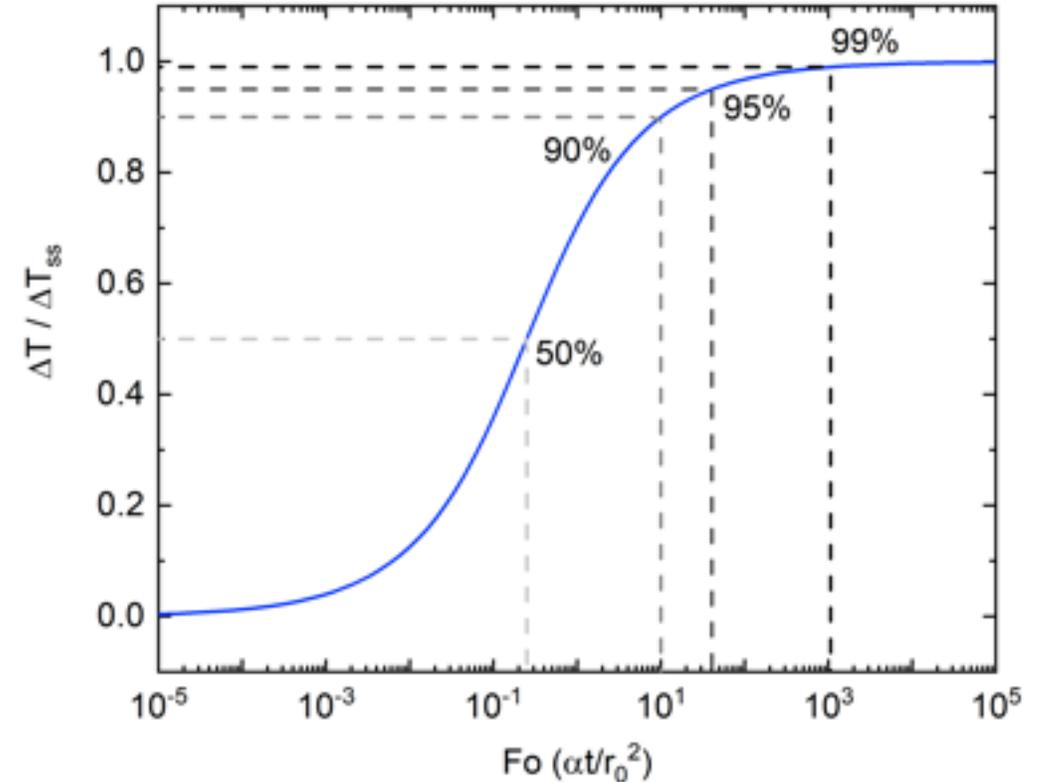
What does “steady-state” mean?

$$q'' = -\kappa \nabla T$$

Heat flux in

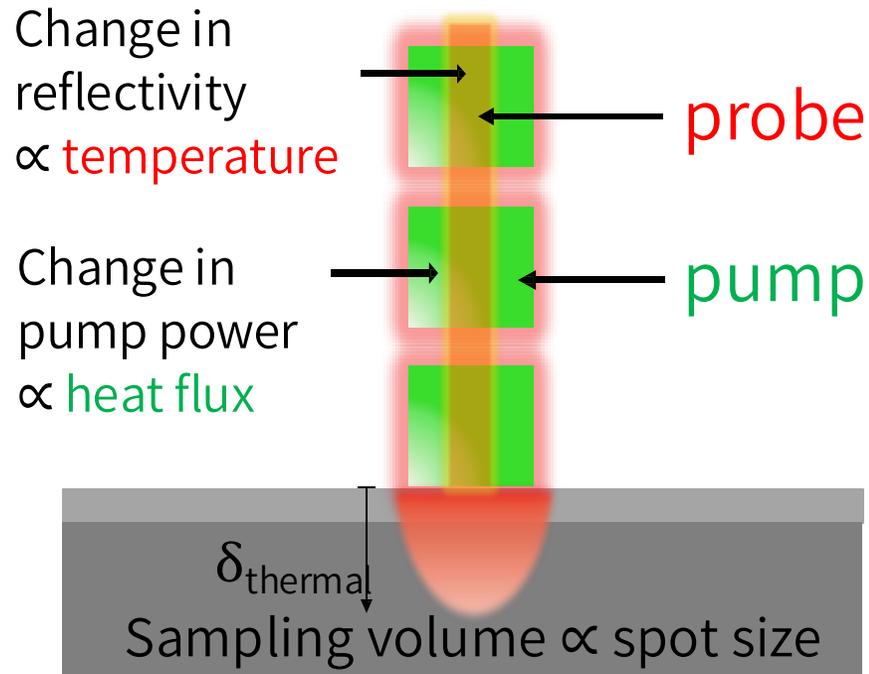


= Heat flux out

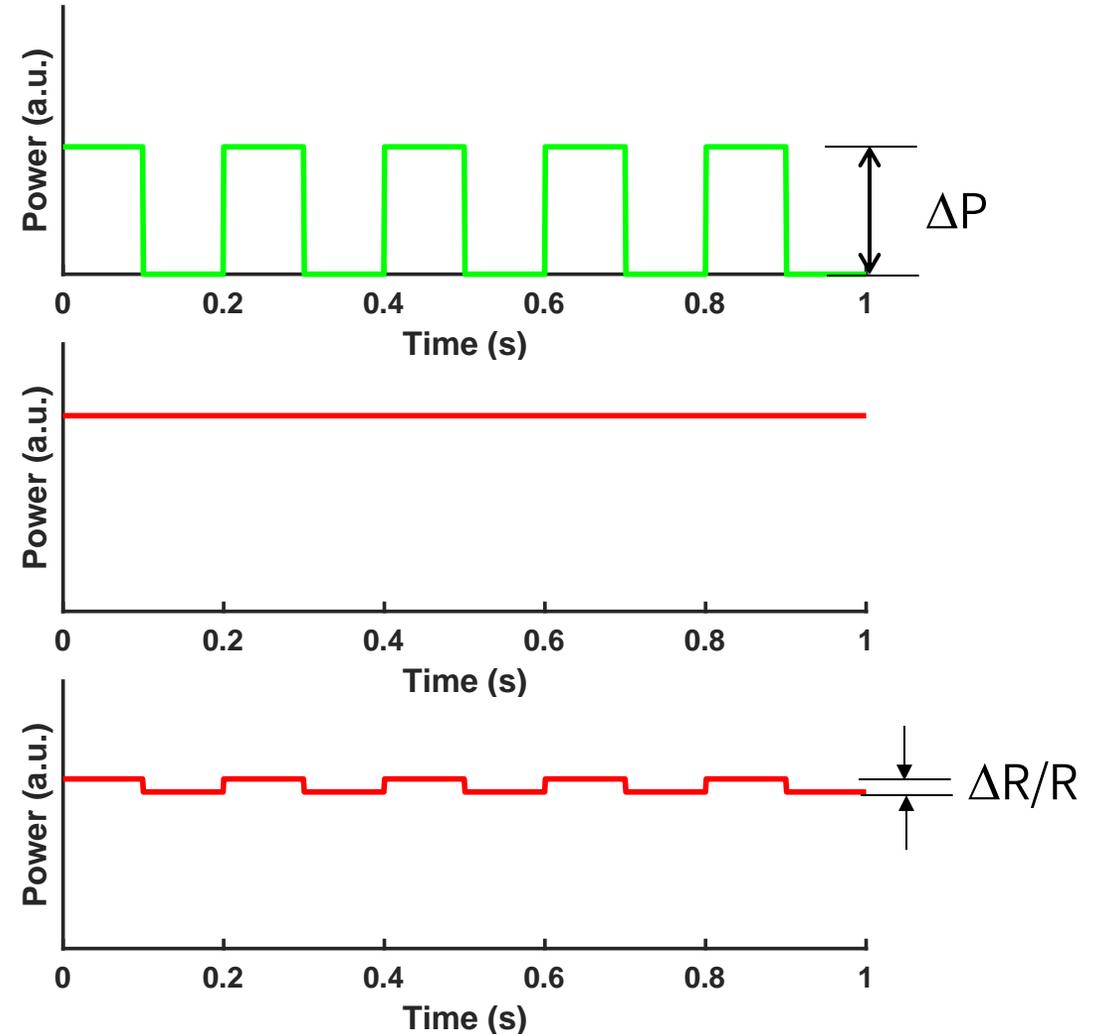


$\alpha$  = Thermal diffusivity  
 $r_0$  =  $1/e^2$  radius of laser

Measurement Concept: Heat a small volume of the sample to a steady-state temperature, measure  $\Delta T$  between “on” and “off” state



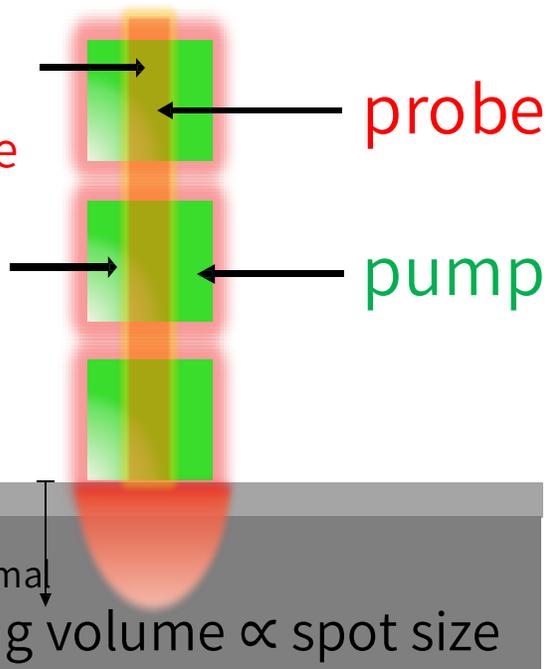
Depth measurement proportional to spot size  
Spot size can be as small as  $<1$  micron



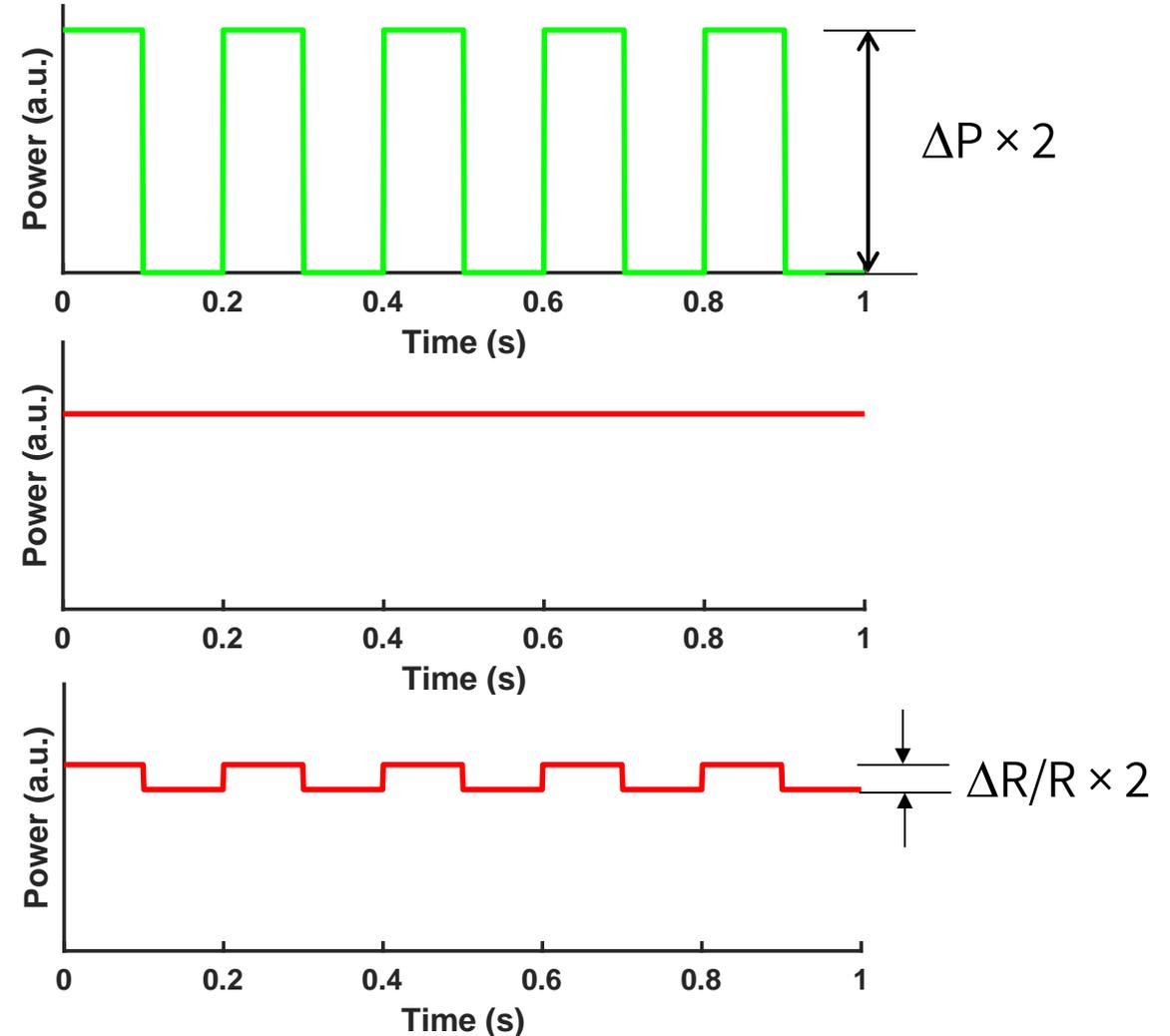
Measurement Concept: Heat a small volume of the sample to a steady-state temperature, measure  $\Delta T$  between “on” and “off” state

Change in reflectivity  $\propto$  temperature

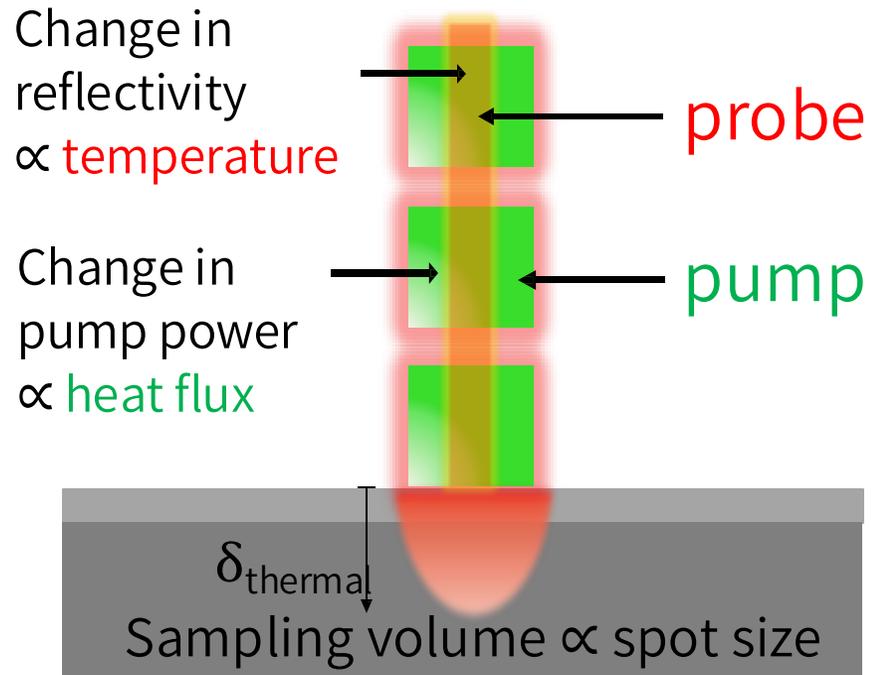
Change in pump power  $\propto$  heat flux



Depth measurement proportional to spot size  
Spot size can be as small as <1 micron



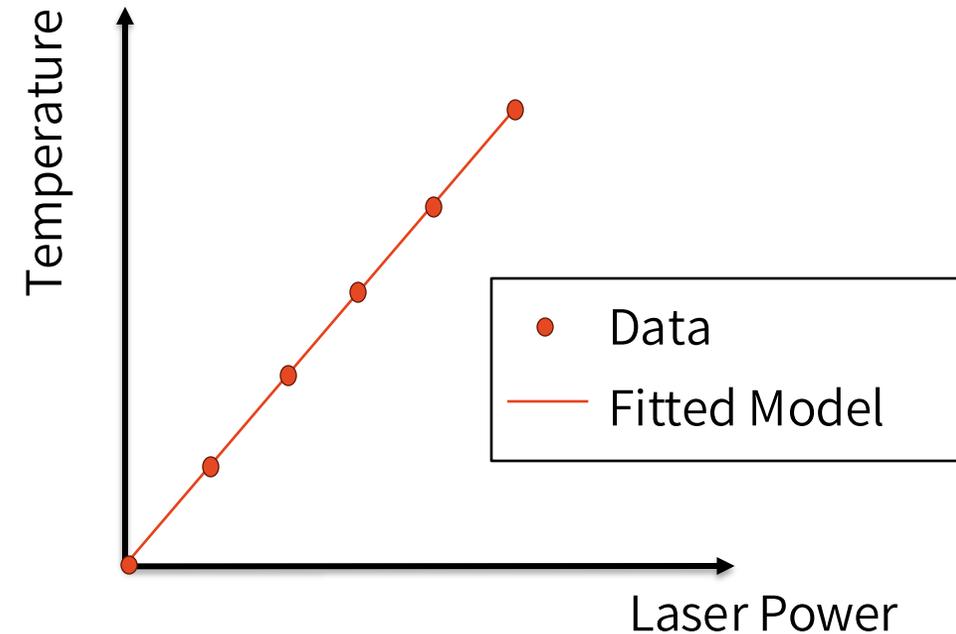
Measurement Concept: Repeat process with multiple powers to improve accuracy



Depth measurement proportional to spot size  
Spot size can be as small as <1 micron

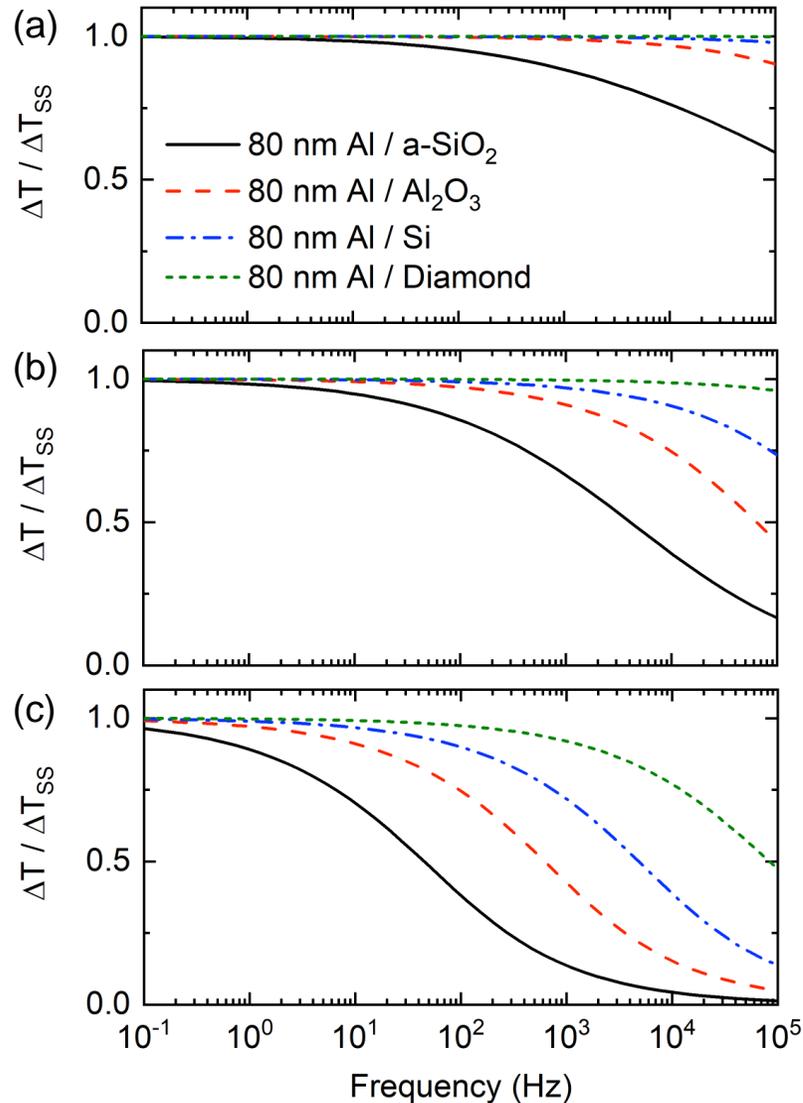
Fourier's Law

$$q'' = -\kappa \nabla T$$



Increasing laser power leads to increasing temperature rise  
Slope of this relation gives us thermal conductivity

Laser Diameter



Goal: **Heat at a low enough frequency to induce a steady-state temperature rise**

$$Q \propto e^{i\omega t} \rightarrow T \propto e^{i\omega t}$$

For some conditions,  $T$  is not in a steady-state  
 $\rightarrow$  Must include for  $\omega$  in the thermal model

Even if sample is in steady-state, it is best practice to include  $\omega$  in thermal model

- Temperature rise is proportional to photodetector voltage

$$\Delta T \propto \frac{\Delta R}{R} \propto \frac{\Delta V}{V}$$

- Linear relation with small temperature changes
- Heat flux proportional to pump power

$$|\Delta q''| \propto \Delta P$$

- Therefore, we can claim

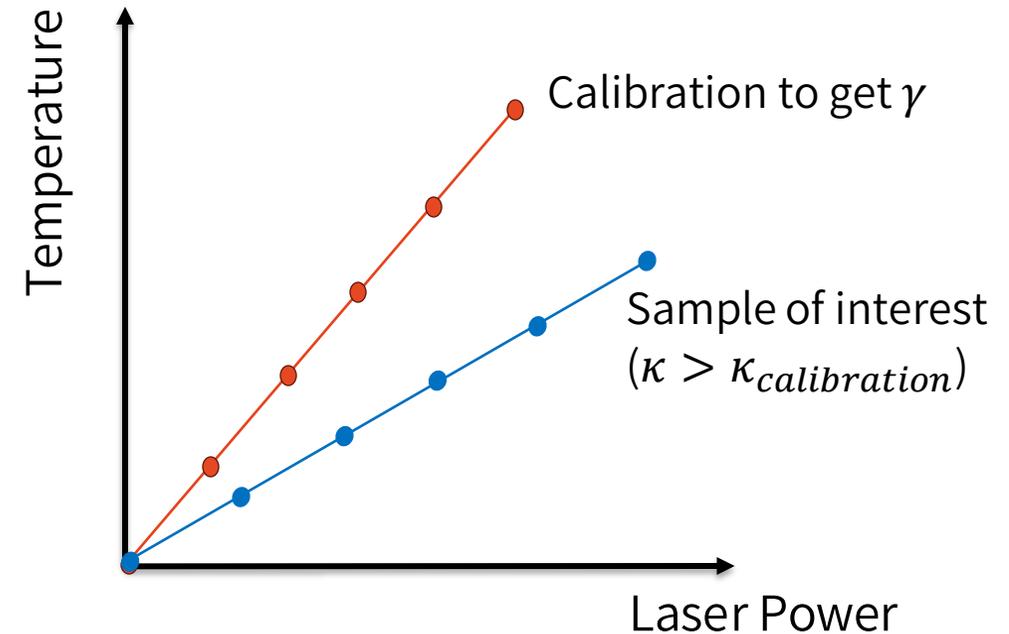
$$\left(\frac{\Delta V}{V \Delta P}\right) = \gamma \left(\frac{\Delta T(\kappa)}{\Delta |q''|}\right)$$

- Use a Calibration to get  $\gamma$

$$\gamma = \left(\frac{\Delta V}{V \Delta P}\right)_{\text{cal}} \left(\frac{\Delta T(\kappa_{\text{cal}})}{\Delta |q''|}\right)^{-1}$$

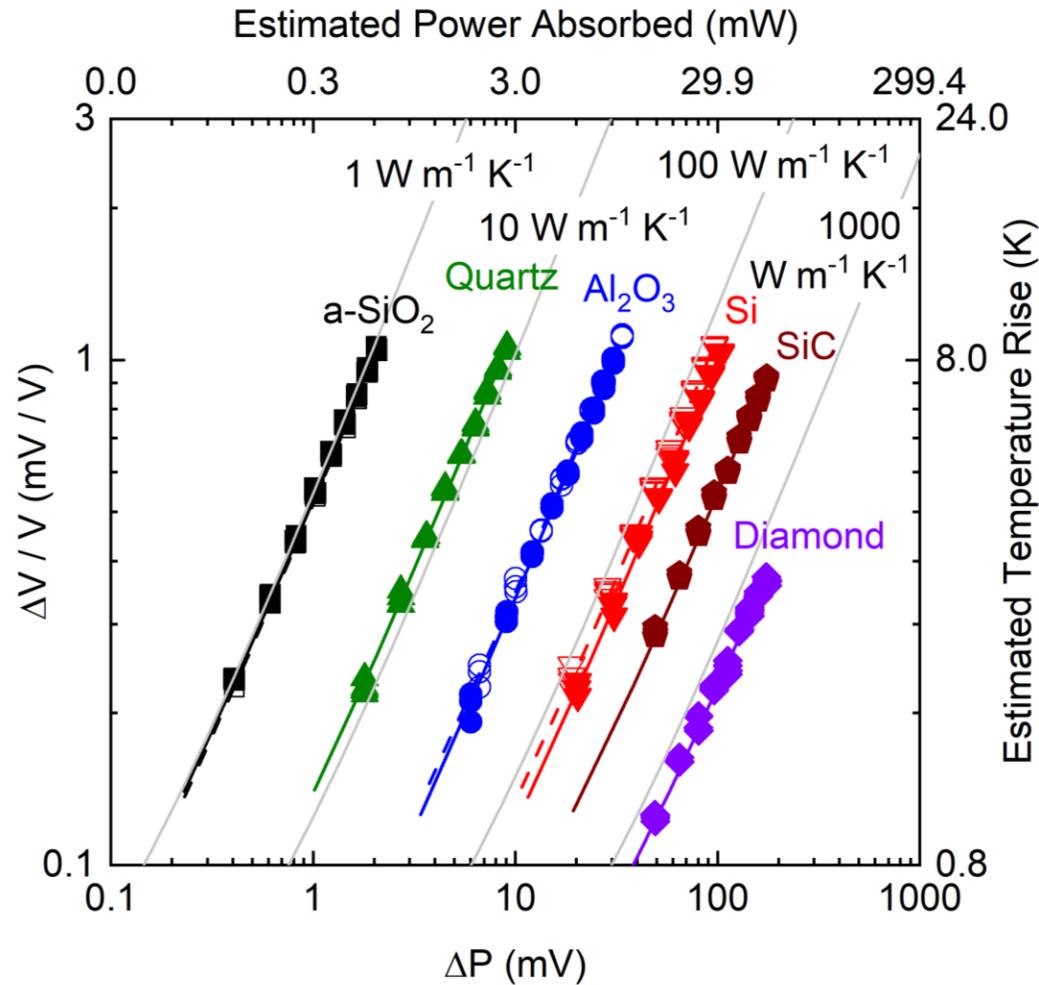
## Fourier's Law

$$q'' = -\kappa \nabla T$$

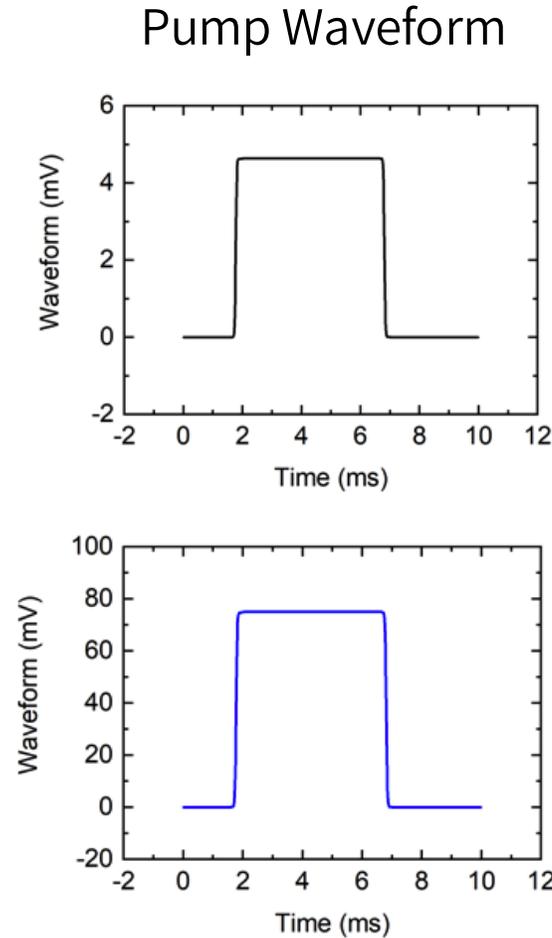


Increasing laser power leads to increasing temperature rise  
Slope of this relation gives us thermal conductivity

## Lock-in Amplifier

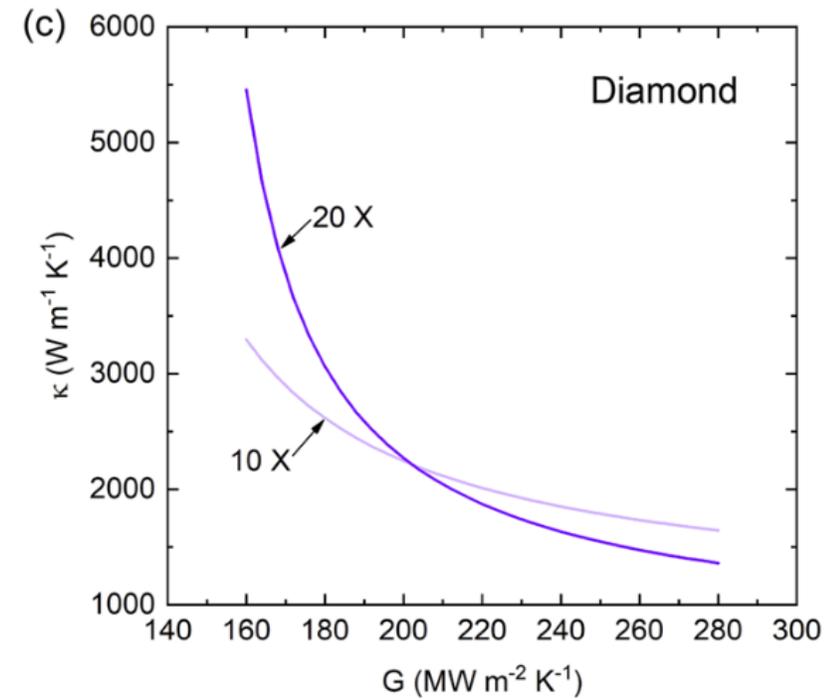
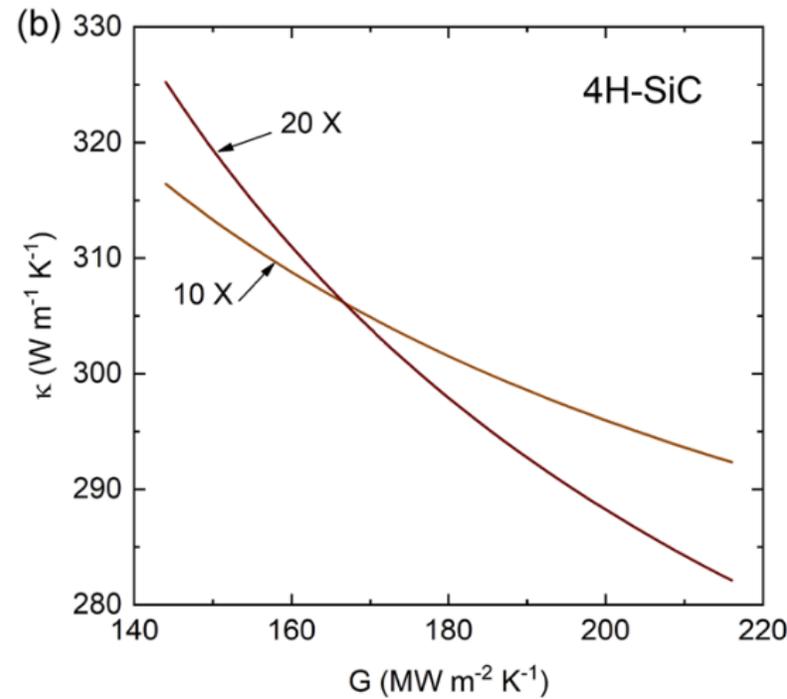
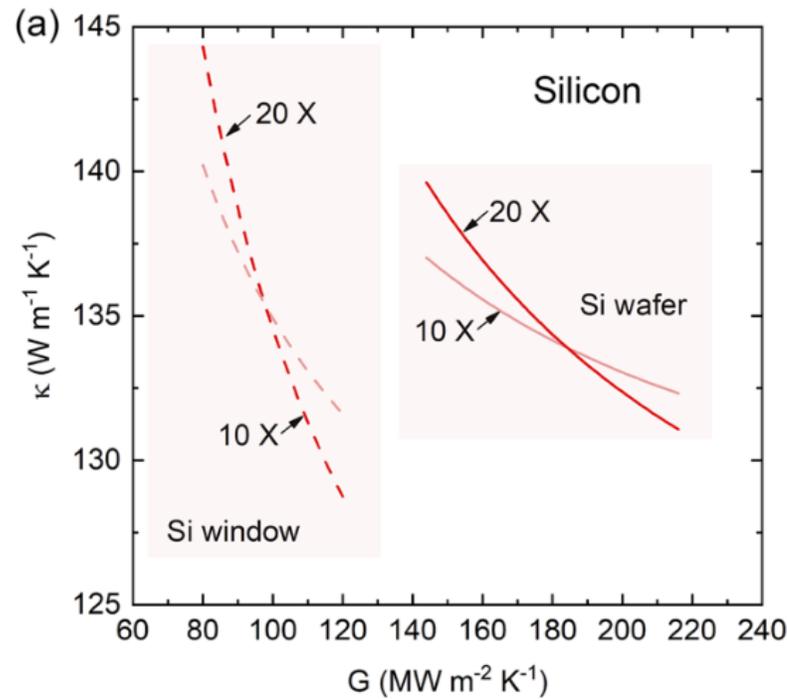


## Periodic Waveform Analyzer with Boxcar Averager



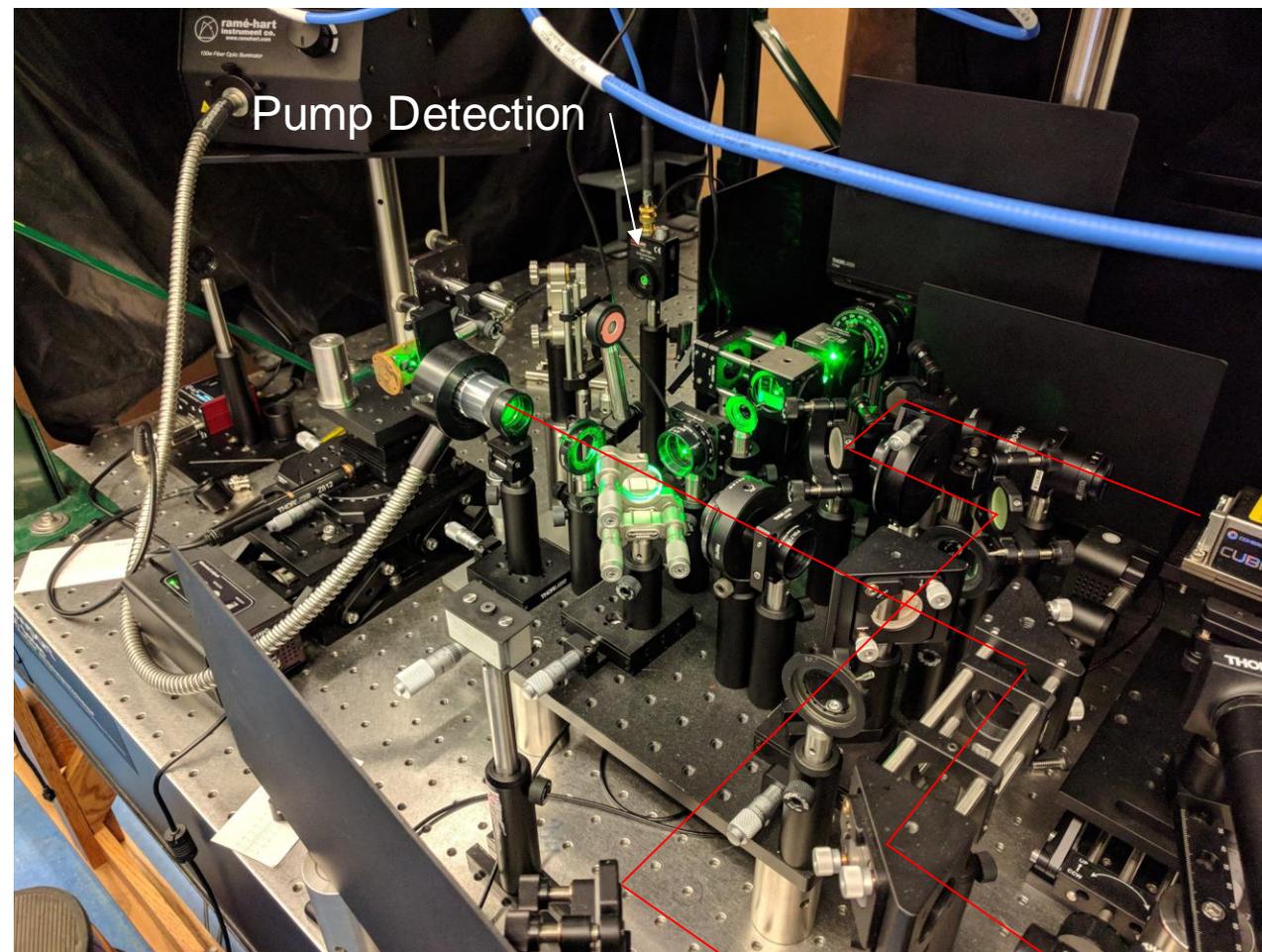
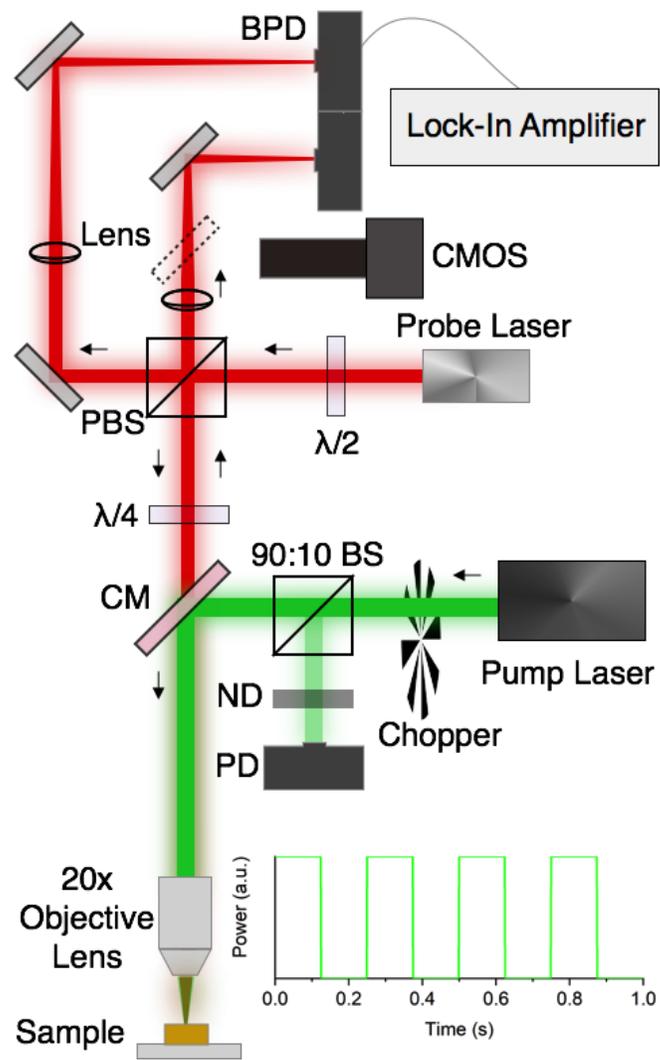
What about thermal boundary conductance (G)?

- Can be significant for high- $\kappa$  materials ( $\kappa > 100 \text{ W/m-K}$ )
- Using different laser diameters allows measurement of both  $\kappa$  and G



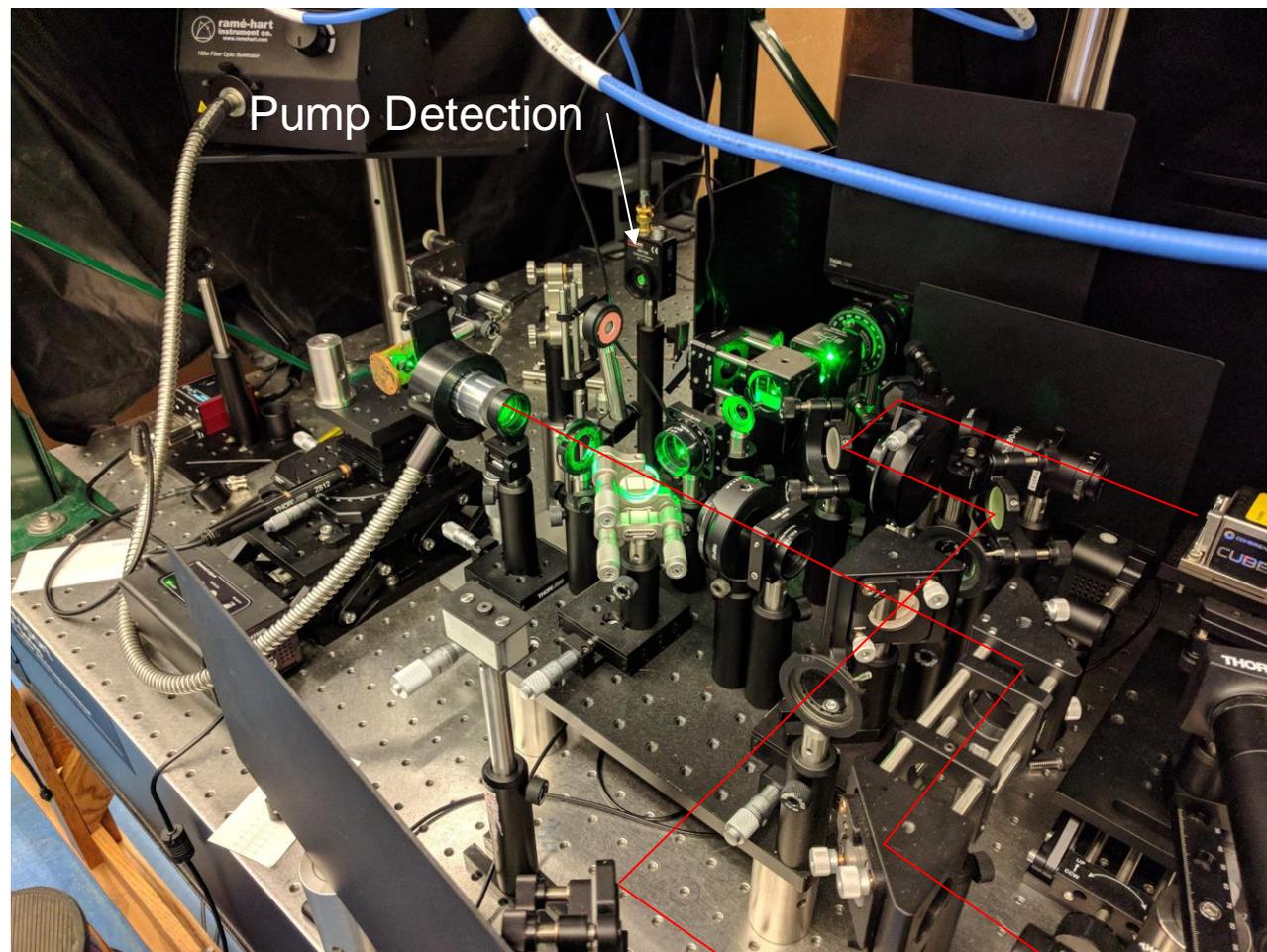
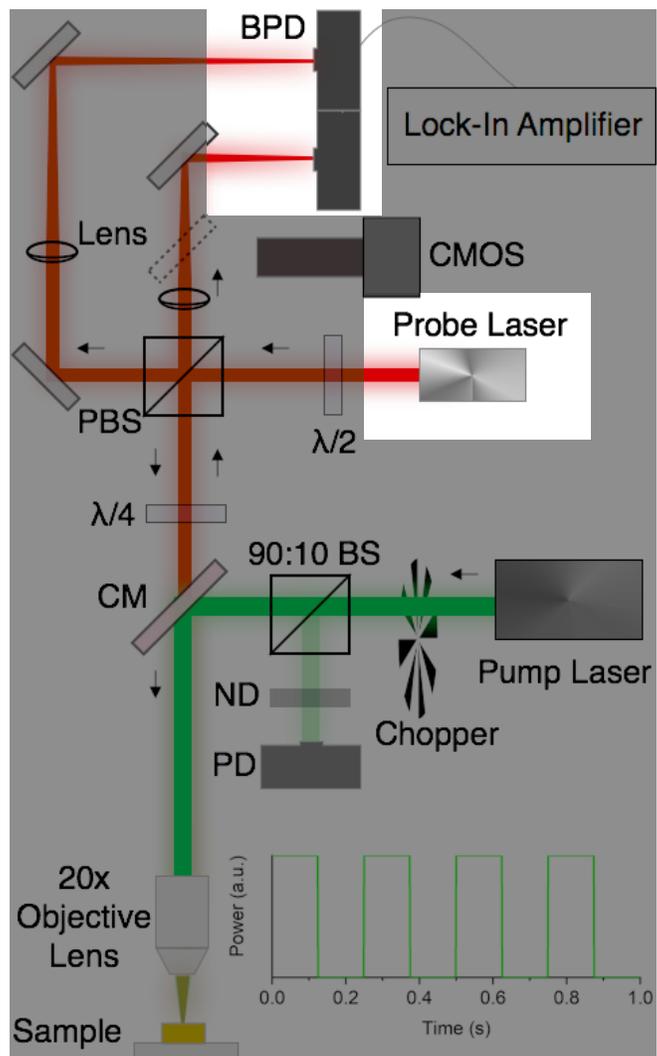
# How to build an SSTR free-space system

# Steady-State Thermoreflectance (SSTR)



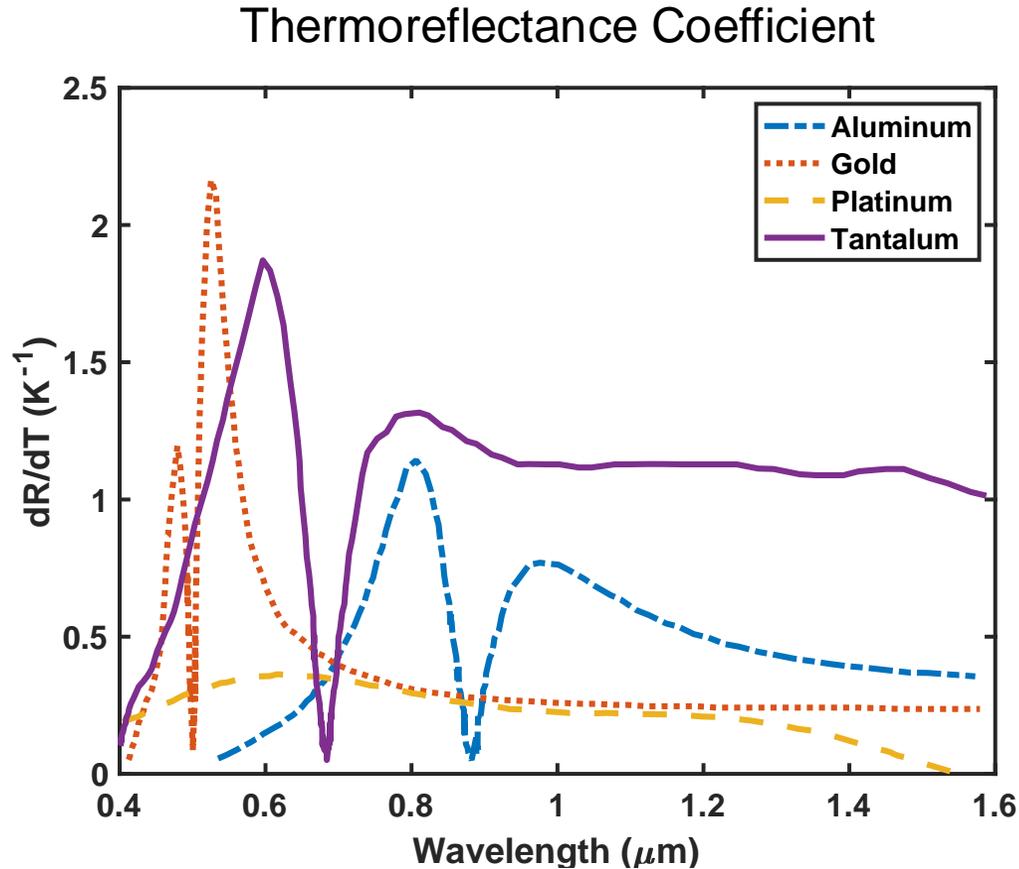
Reference Probe

# Steady-State Thermoreflectance (SSTR)



Reference Probe

Selecting Probe Wavelength: let's choose Aluminum as our transducer



Fourier's Law

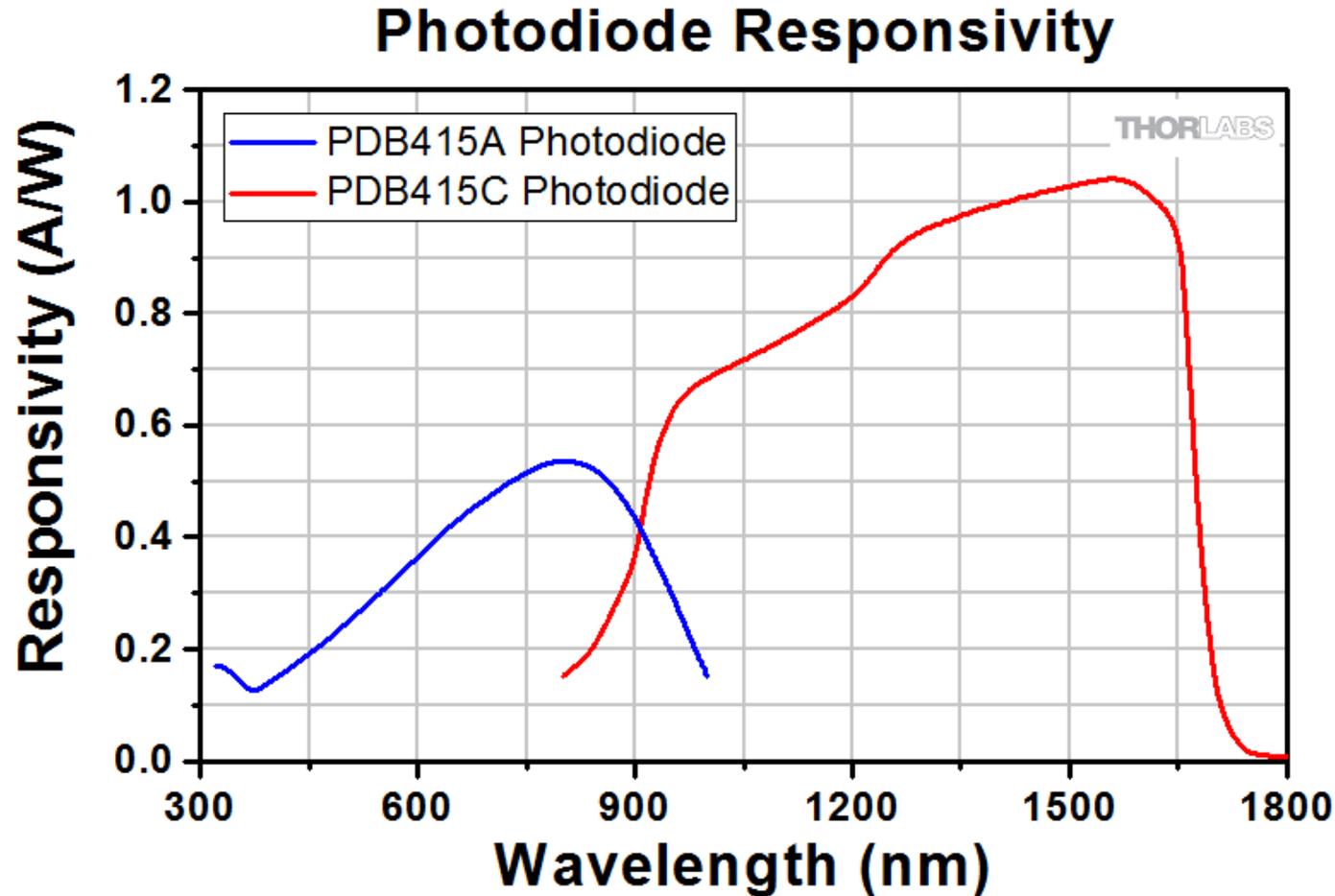
$$q'' = -\kappa \nabla T$$

$$\Delta V_{Probe} \propto \beta(\lambda) D(\lambda) \Delta T$$

$\beta(\lambda)$  = Thermoreflectance Coefficient

$D(\lambda)$  = Detector Responsivity

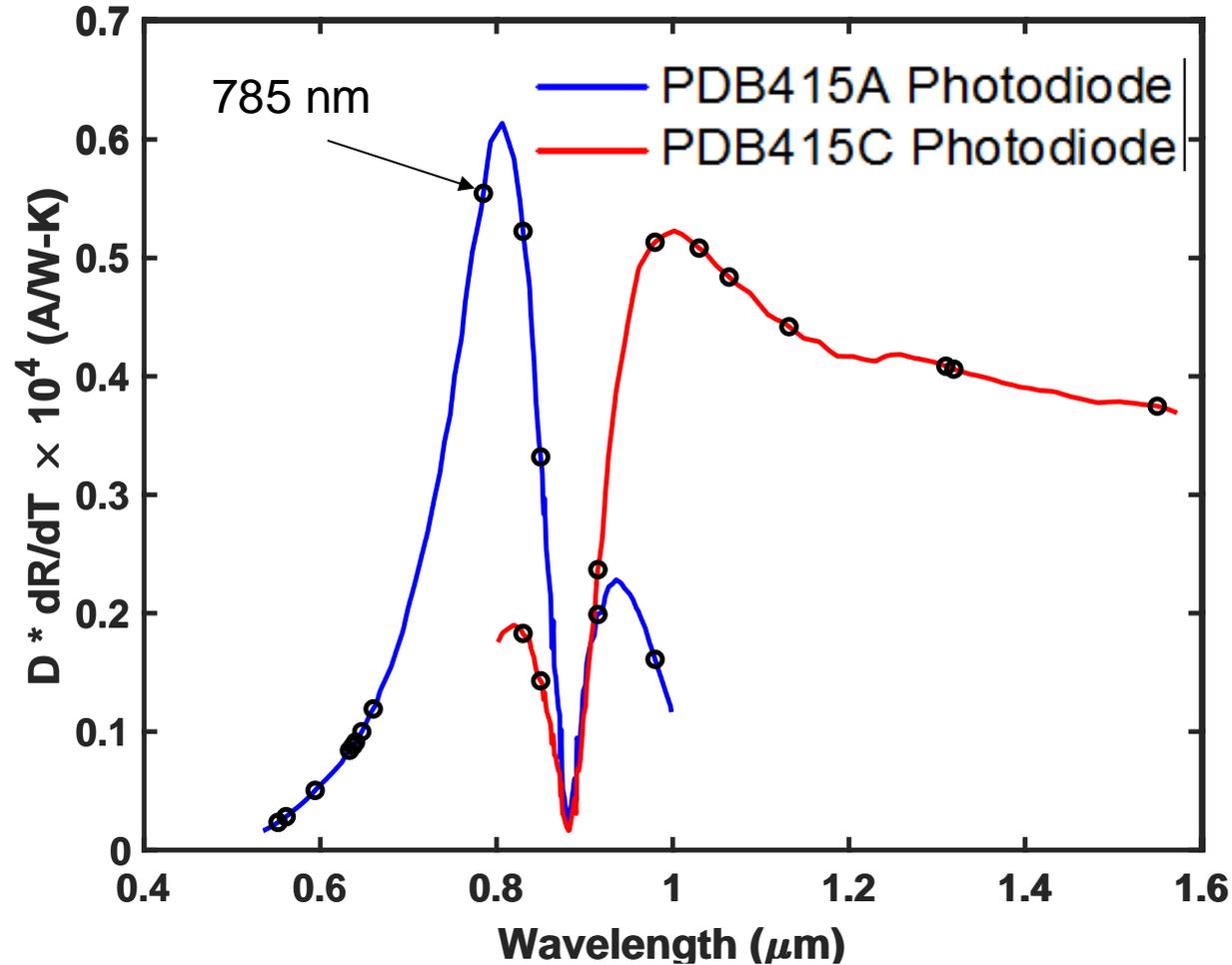
## Photodetector Responsivity



<https://www.thorlabs.com>

Item #	PDB415A	PDB415C
Detector Type	Si/PIN	InGaAs/PIN
Wavelength Range	320 - 1000 nm	800 - 1700 nm
Typical Max Responsivity	0.53 A/W	1.0 A/W
Active Detector Diameter	0.8 mm	0.3 mm
Bandwidth (3 dB)	DC - 100 MHz	
Common Mode Rejection Ratio	>25 dB	
Transimpedance Gain <sup>a</sup>	50 x 10 <sup>3</sup> V/A	
Minimum NEP <sup>b</sup>	12.03 pW/Hz <sup>1/2</sup> (DC - 100 MHz)	6.99 pW/Hz <sup>1/2</sup> (DC - 100 MHz)
RF Output Conversion Gain <sup>a,c</sup>	26.5 x 10 <sup>3</sup> V/W	50 x 10 <sup>3</sup> V/W
CW Saturation Power	135 μW @ 820 nm	72 μW @ 1550 nm

## Probe Figure of Merit as a function of probe laser wavelength

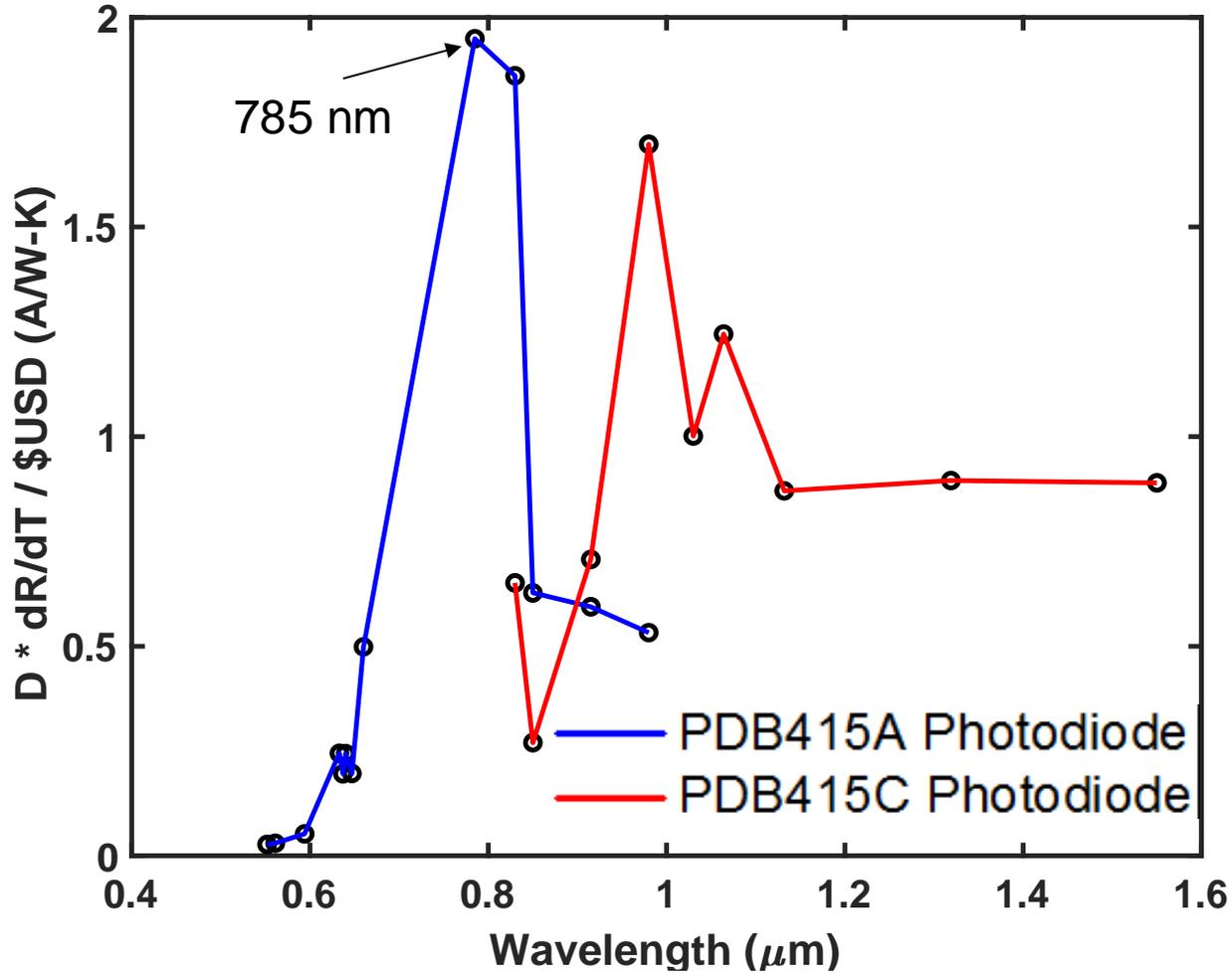


## Commonly Available Laser Wavelengths

OBIS	Matchbox
	375
	405
	445
	458
	473
	488
	505
	514
	520
	532
	552
	561
	594
	633
	637
	640
	647
	660
	785
	830
	850
	915
	980
	1030
	1064
	1123
	1319
	1550

What about cost?

**Conclusion: 785 nm is best option for probe**



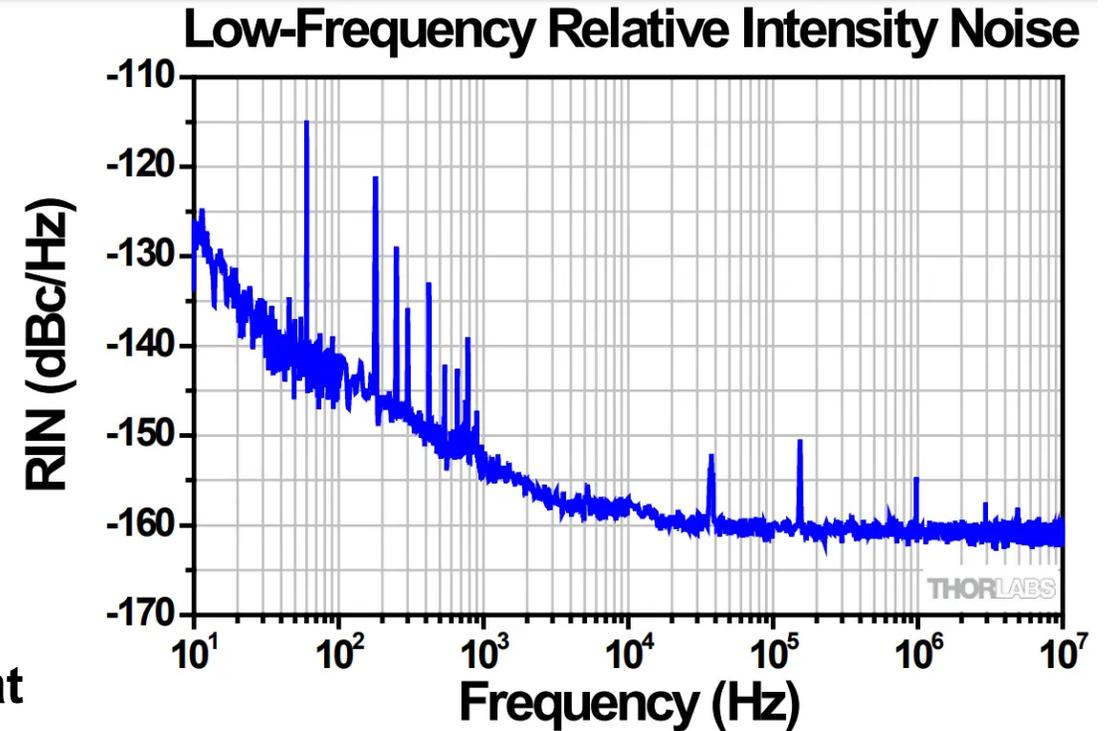
Available Laser Wavelengths

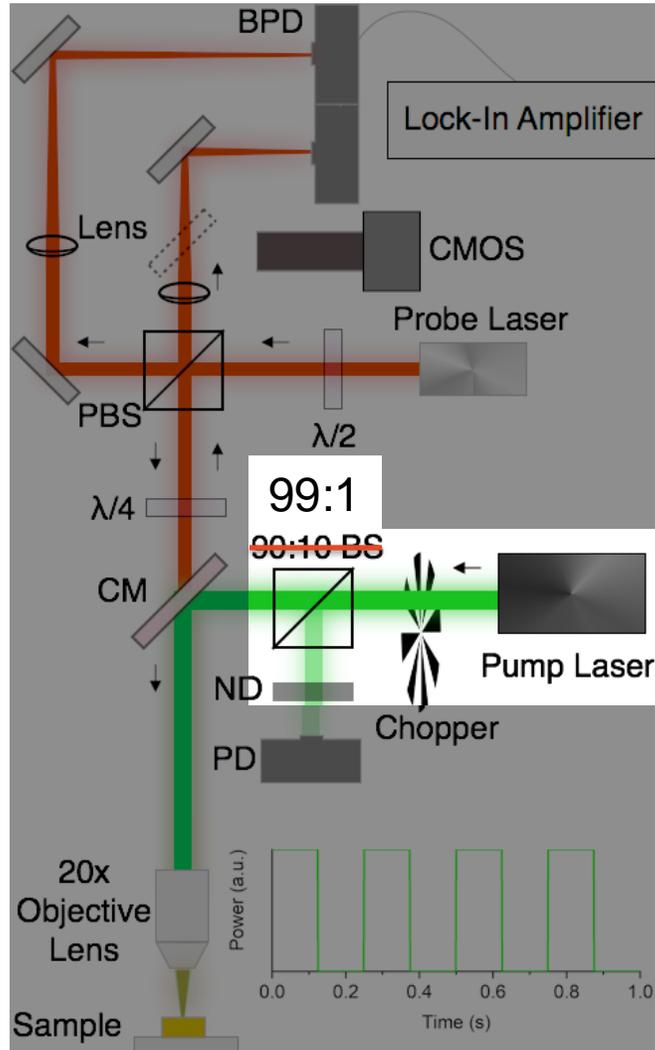
OBIS	Matchbox
	375
	405
	445
	458
	473
	488
	505
	514
	520
	532
	552
	561
	594
	633
	637
	640
	647
	660
	785
	830
	850
	915
	980
	1030
	1064
	1123
	1319
	1550

Some final notes on probe noise and detection

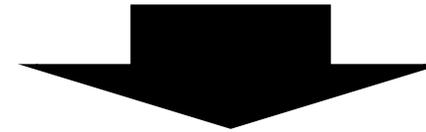
- Balanced photodetector is best performing for low frequency detection
- Path matching probe signal and reference arm does not significantly affect performance
- Probe laser has a noise spectrum
- Detector + lock-in amplifier has a noise spectrum

**Adjust probe power to optimize signal-to-noise at your operating frequency**



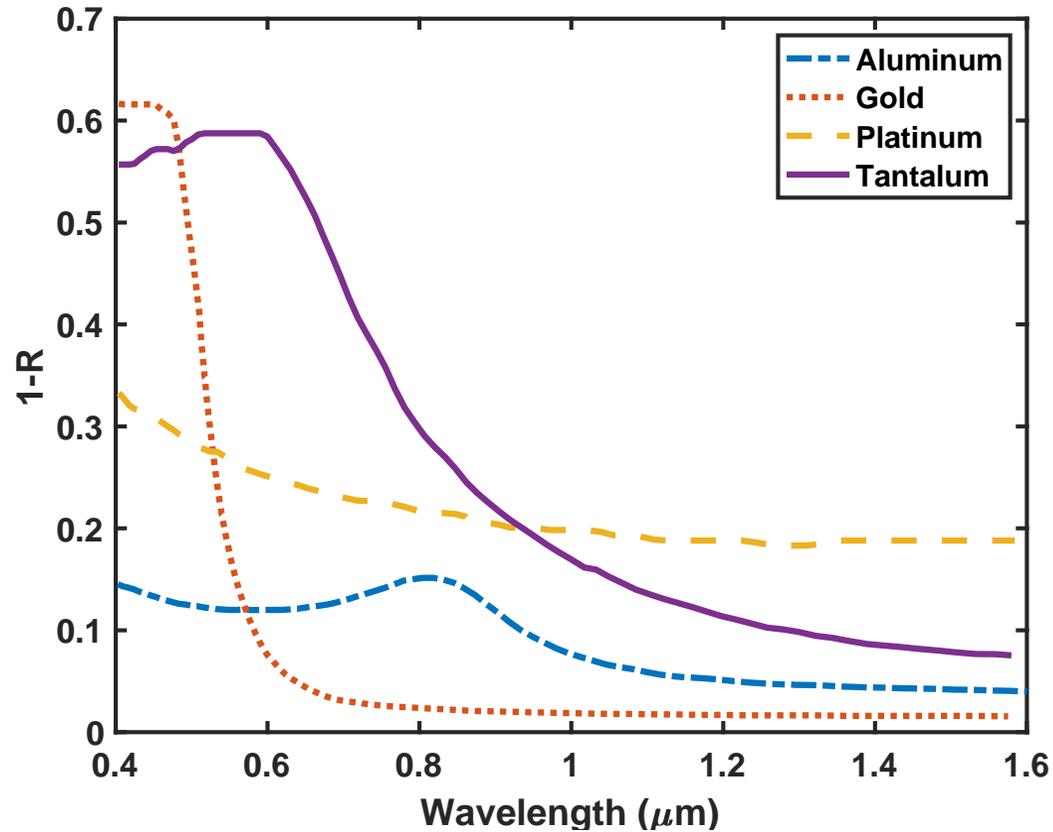


Pump selection comes down to how much *absorbed power* is needed in your sample.



This can be determined based on the the **maximum  $\kappa$**  to be measured

## Selecting Pump Wavelength



Fourier's Law

$$q'' = -\kappa \nabla T$$

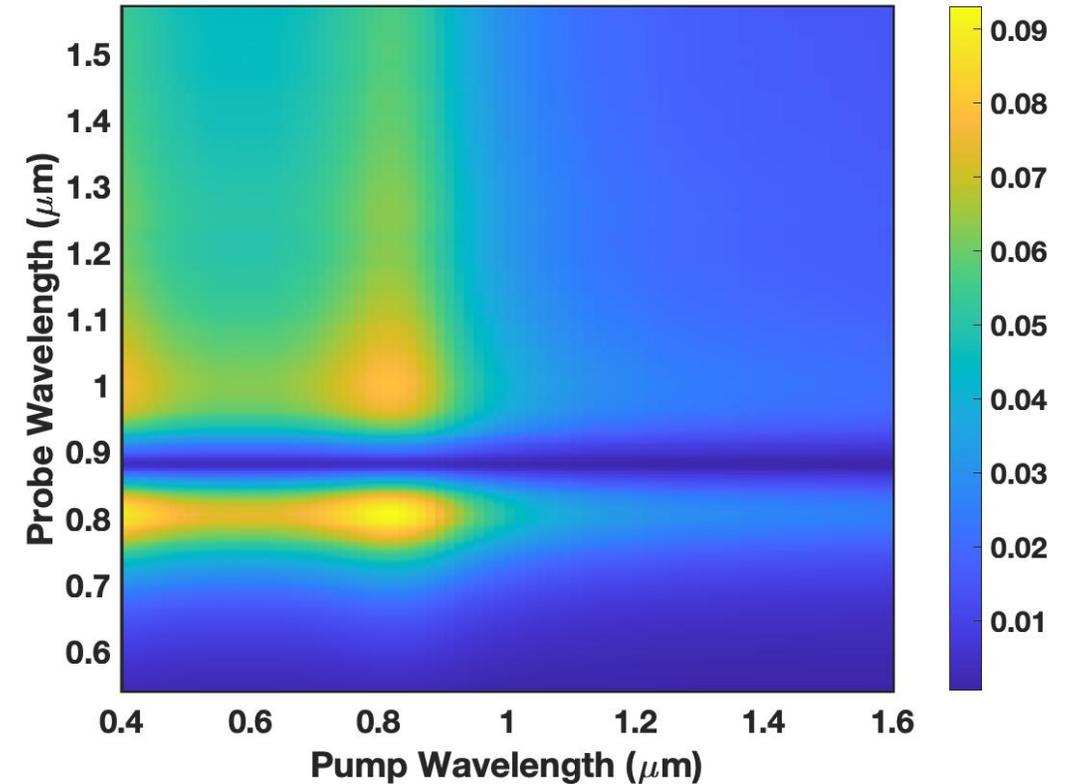
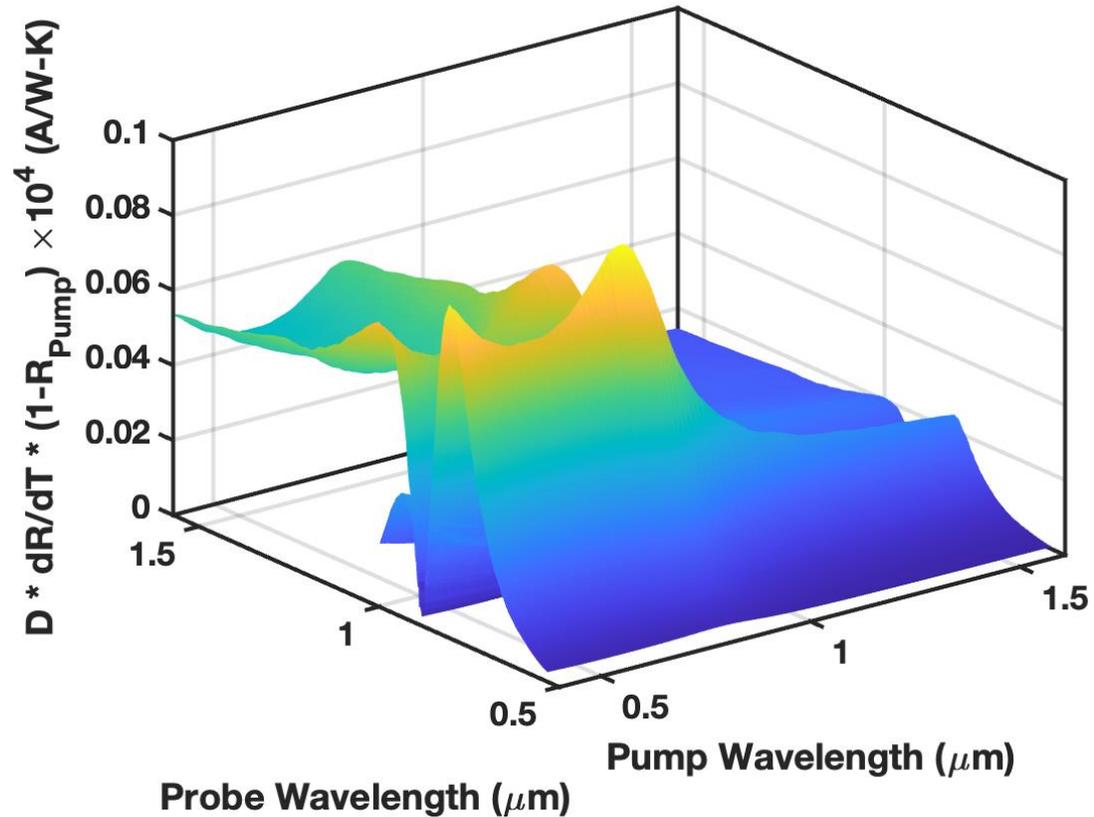
$$\Delta V_{Pump} \propto (1 - R(\lambda))$$

$R(\lambda)$  = Reflectance

Wilson, R. B., et al. *Optics express* 20.27 (2012): 28829-28838.

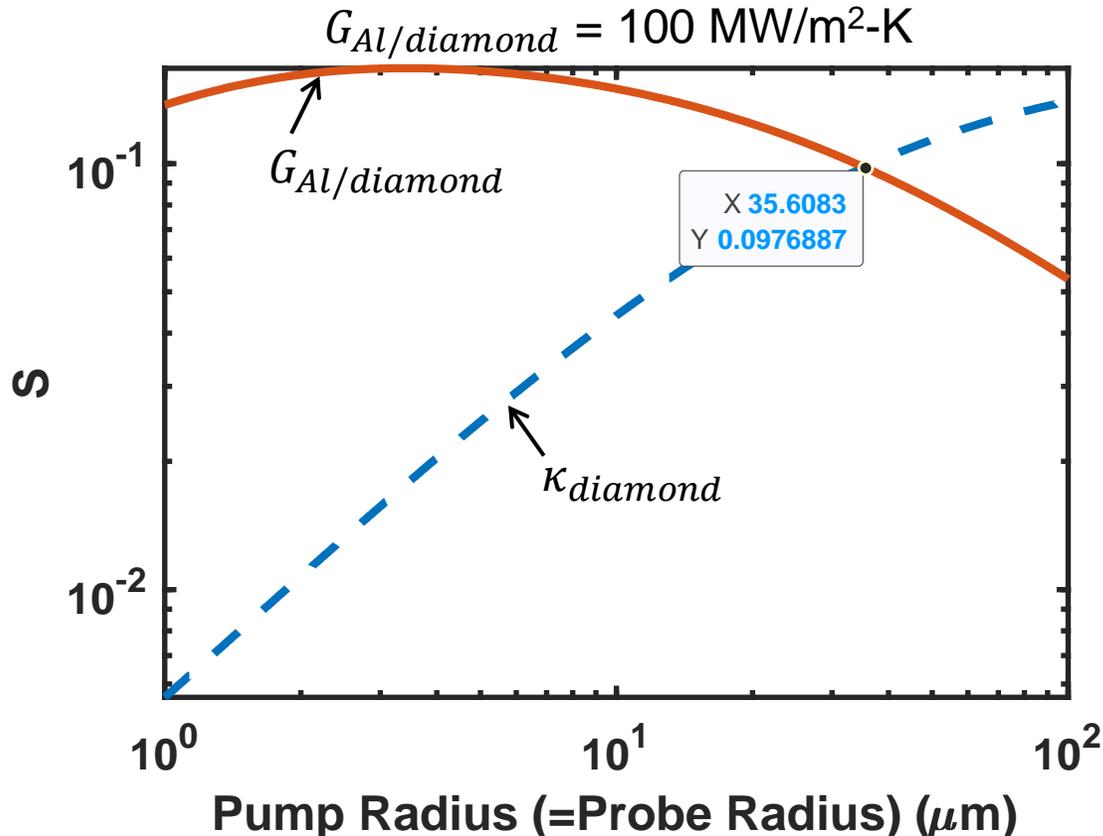
Combined Figure of Merit for selecting pump and probe wavelength

$$\Delta V_{Probe} \propto \beta(\lambda_{probe})D(\lambda_{probe})\Delta T \propto \beta(\lambda_{probe})D(\lambda_{probe})(1 - R(\lambda_{pump}))$$



**Conclusion: ~800 nm wavelength is ideal for both pump and probe**

Consider the hardest case to measure: low G,  $\kappa = 3000$  W/m-K



Measurement Sensitivity

$$S_x = \frac{|T_{1.1x} - T_{0.9x}|}{T_x}$$

Layer 1: Aluminum

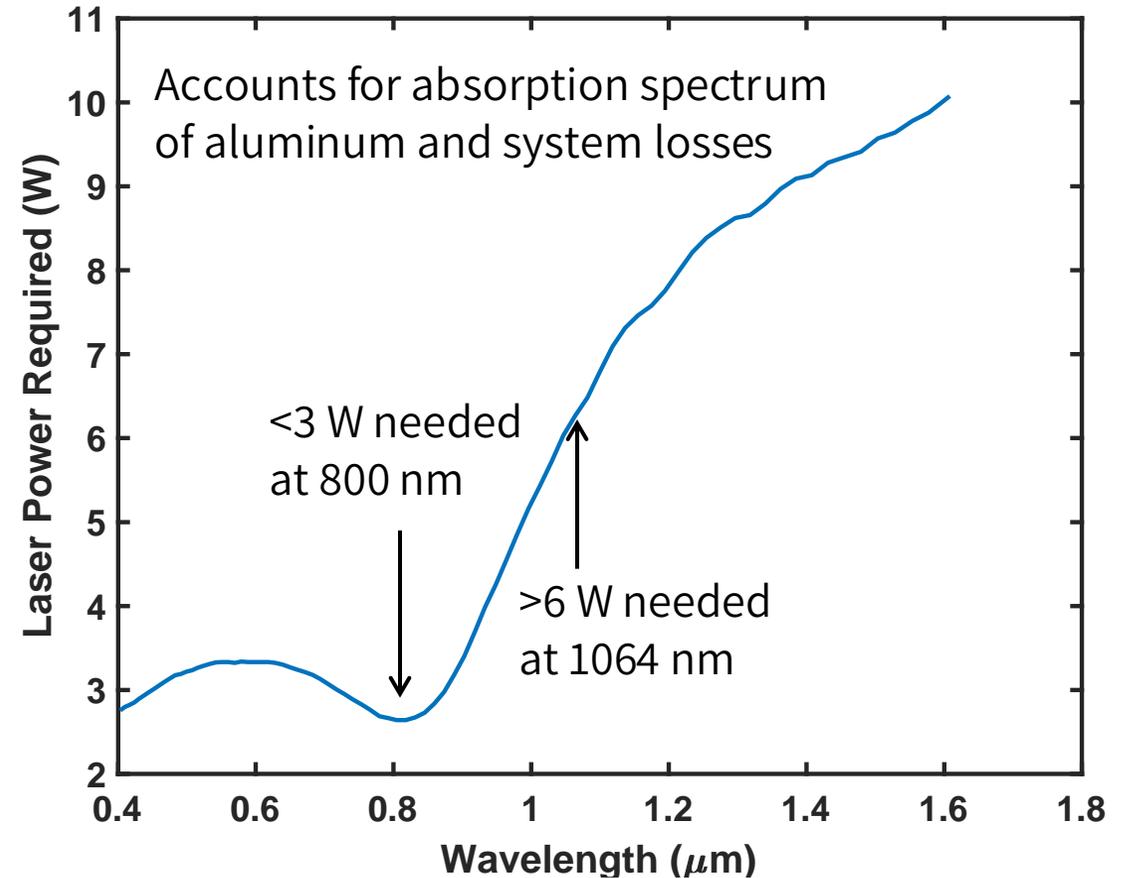
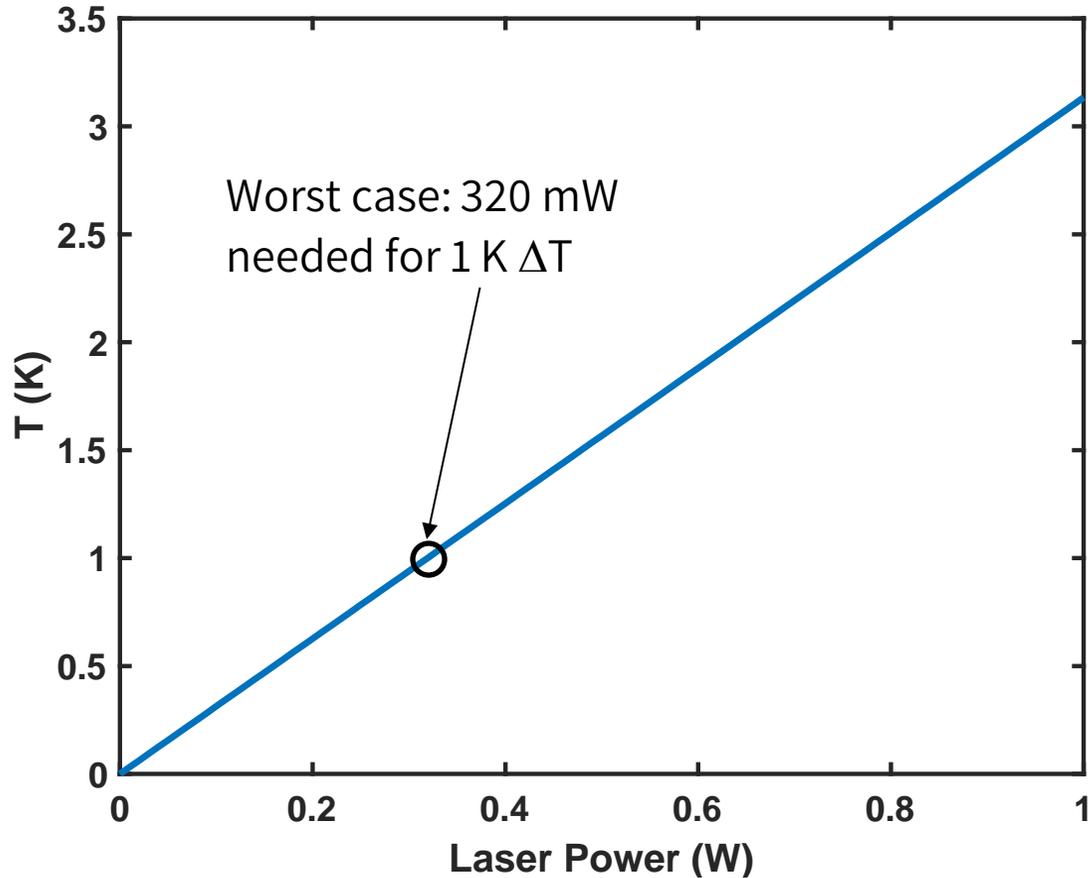
- $\kappa = 180$  W/m-K
- $C_v = 2.42$  J/cm<sup>3</sup>-K
- Thickness = 80 nm

Layer 2: Diamond

- $\kappa = 3000$  W/m-K
- $C_v = 1.78$  J/cm<sup>3</sup>-K

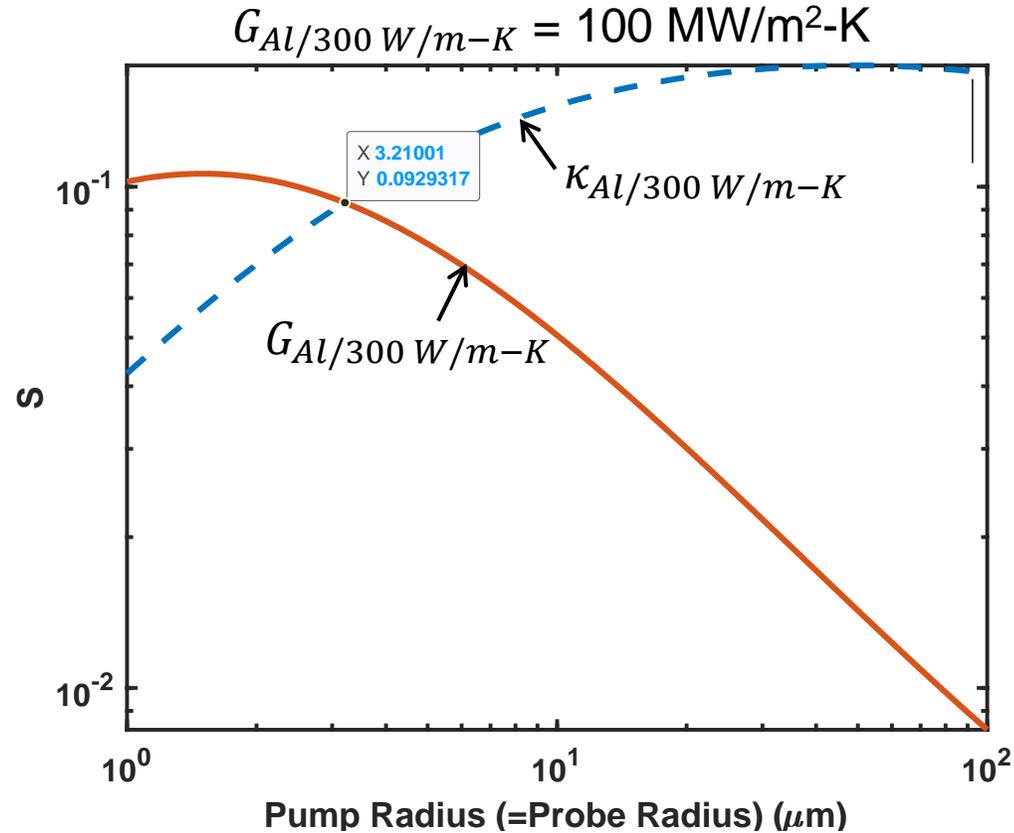
**Worst case: ~35  $\mu$ m radius  $\rightarrow$  assume 50  $\mu$ m to be conservative**

Temperature rise as a function of absorbed pump laser power...



...translates to laser power needed for pump specification

What if we only need a system capable of measuring up to  $\kappa = 300 \text{ W/m-K}$ ?



Measurement Sensitivity

$$S_x = \frac{|T_{1.1x} - T_{0.9x}|}{T_x}$$

Layer 1: Aluminum

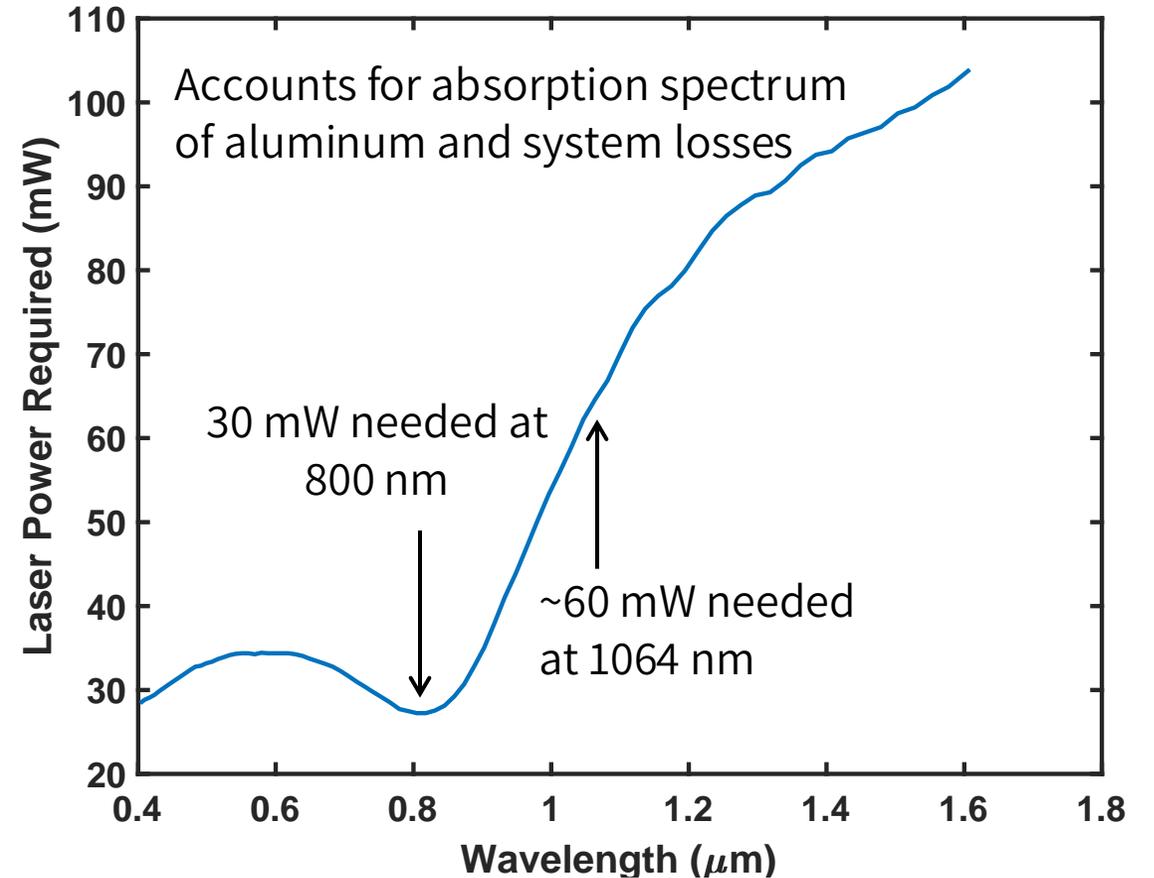
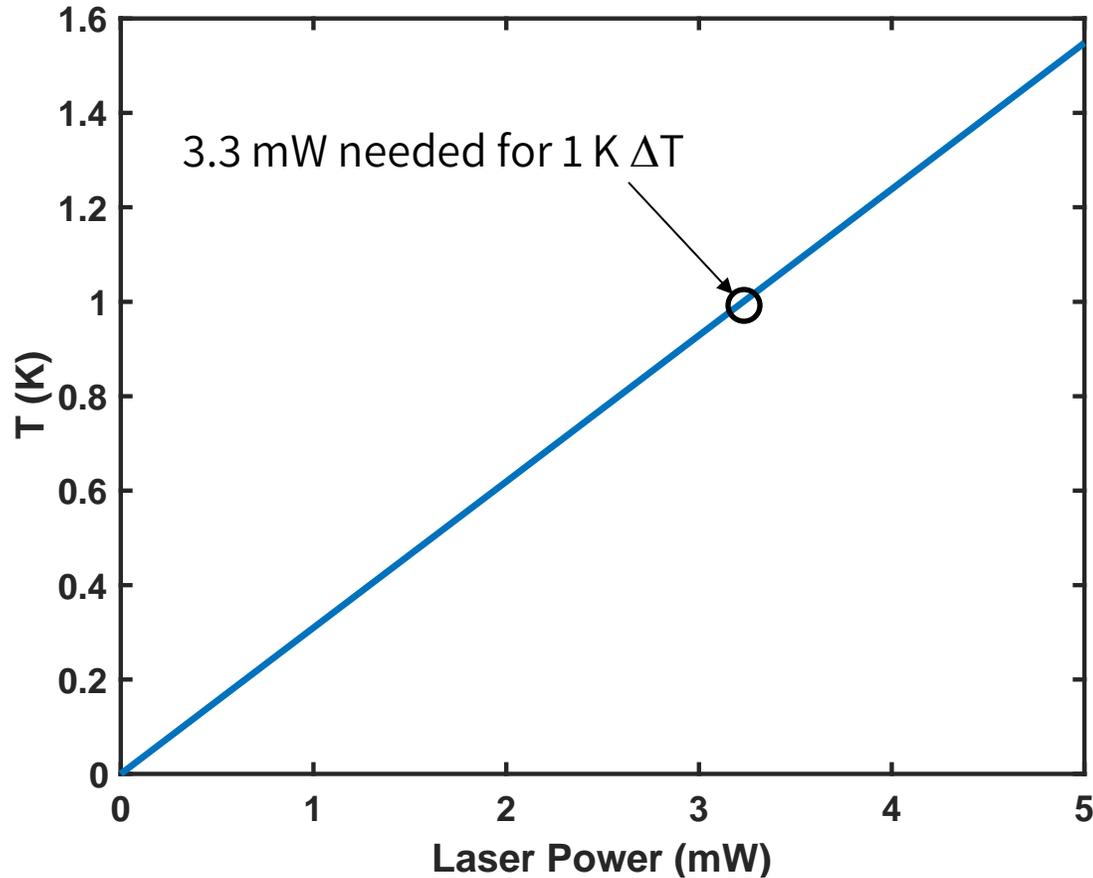
- $\kappa = 180 \text{ W/m-K}$
- $C_v = 2.42 \text{ J/cm}^3\text{-K}$
- Thickness = 80 nm

Layer 2: Diamond

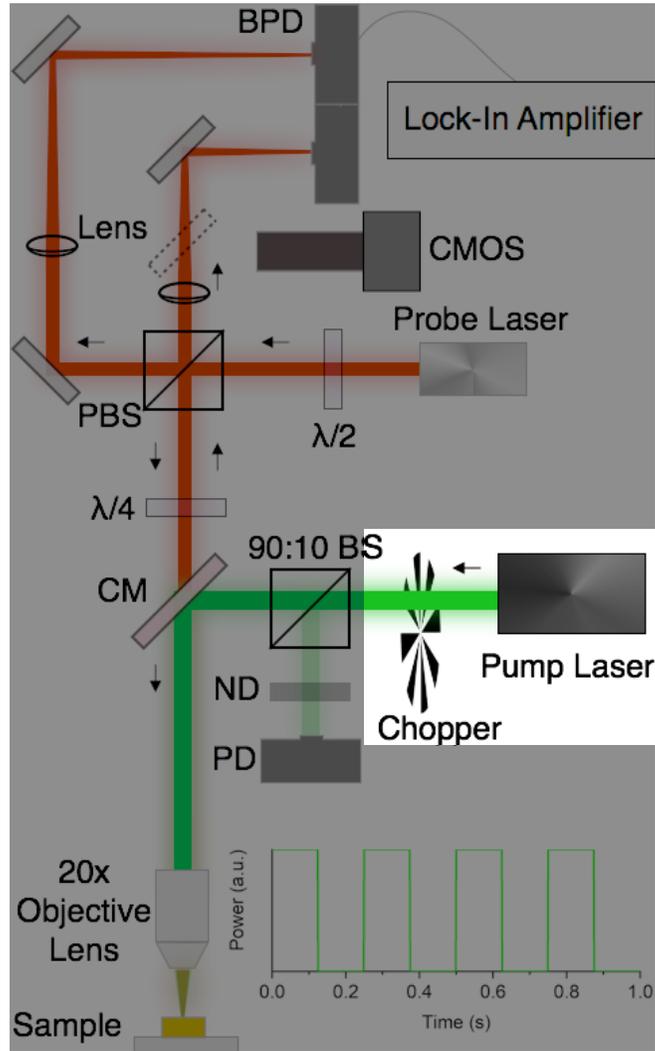
- $\kappa = 300 \text{ W/m-K}$
- $C_v = 1.78 \text{ J/cm}^3\text{-K}$

**Sensitivity crossover  $\sim 3.2 \mu\text{m}$  radius  $\rightarrow$  assume maximum of  $5 \mu\text{m}$  needed**

What if we only need a system capable of measuring up to  $\kappa = 300 \text{ W/m-K}$ ?



Very manageable to obtain – **most FDTR systems can be converted to SSTR mode!**



## Pump Modulation Options

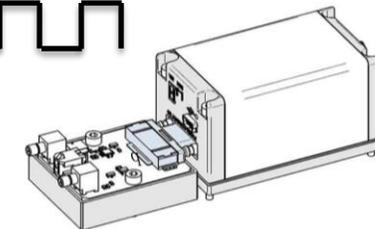
Mechanical Chopper



Electro-Optic or Acousto-Optic Modulator

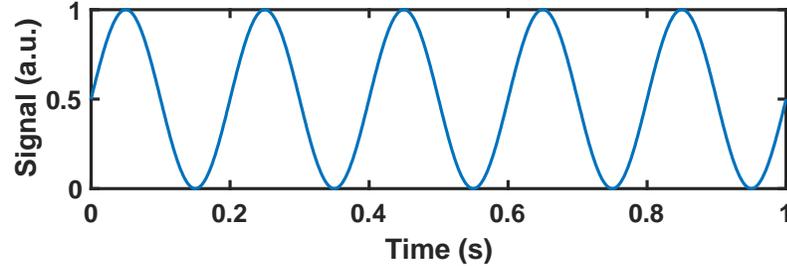
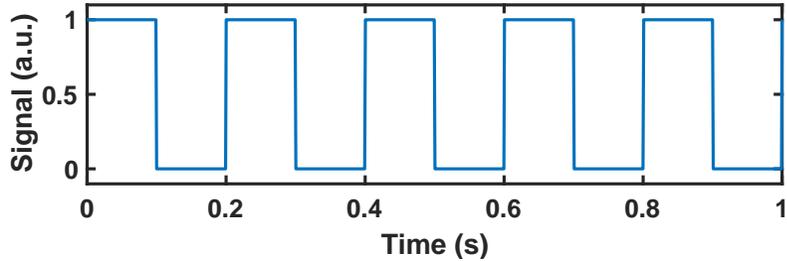


Drive Current Modulation



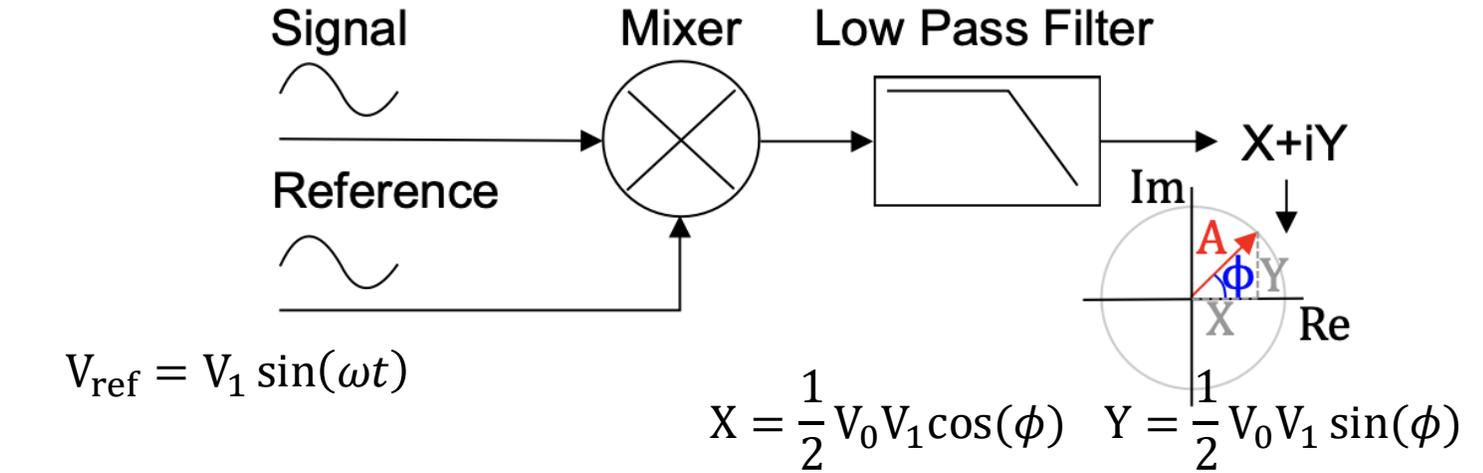
Does modulation waveform matter?

**Depends on demodulator! For sine wave demodulation, no.**



$$V_{\text{sig}} = V_0 [\sin(\omega t + \phi) + f(t)]$$

$$V_{\text{sig}} \times V_{\text{ref}} = \frac{1}{2} V_0 V_1 [\cos(2\omega t + \phi) + \sin(\omega t) f(t) + \cos(\phi)]$$

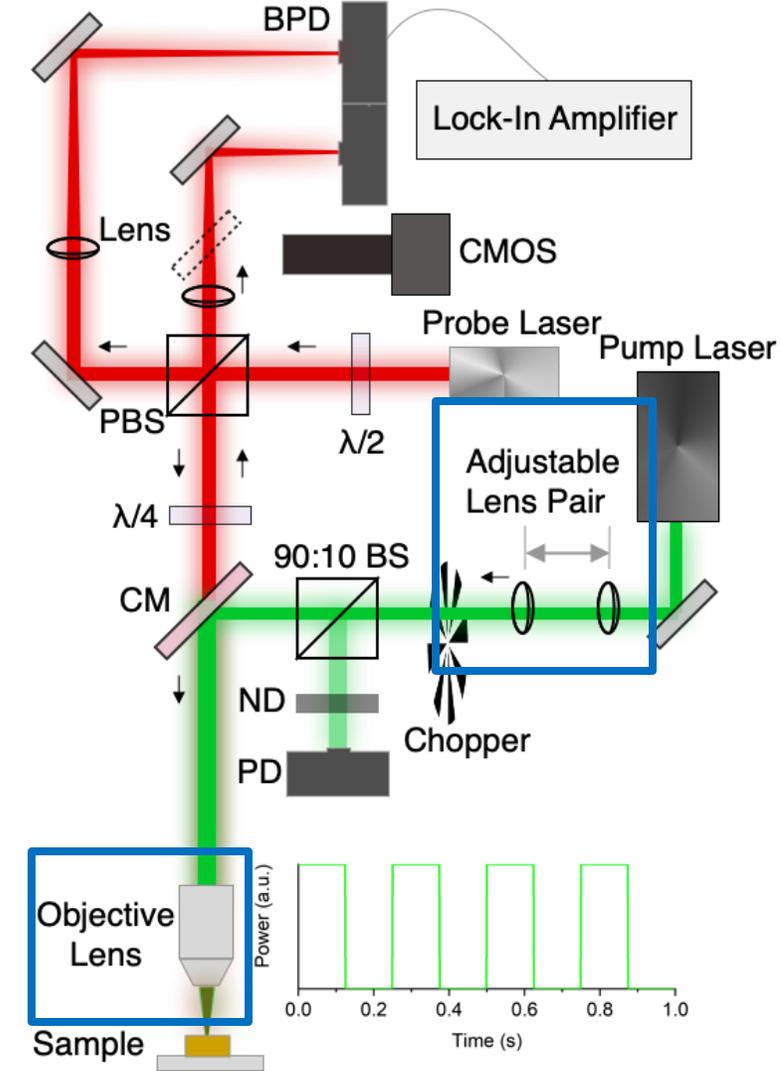
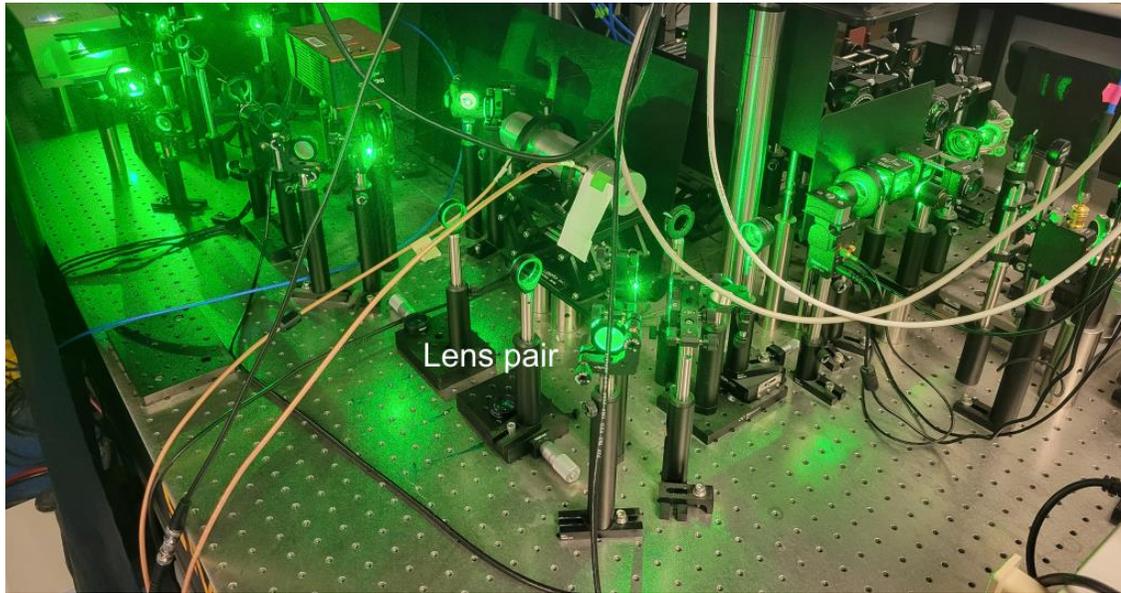


Recommendation:

- For lock-in amplification, drive and demodulate with sine wave
  - For chopper, only square wave is possible → still demodulate with sine wave

# How to adjust pump laser spot size

- Adjustable lens pair allows changing spot size of pump
- Common objective lenses available for different magnification at sample
  - 2x
  - 5x
  - 10x
  - 20x
  - 50x



Does  $\gamma$  change with modulation frequency?

- Generally no, as long as you remain below detector bandwidth

Does  $\gamma$  change with temperature?

- Yes, near linear relationship for Al transducer
- No significant change for Au transducer

Does  $\gamma$  change with each transducer deposition?

- Generally no, but best practice is to include a calibration sample

Does  $\gamma$  change day-to-day?

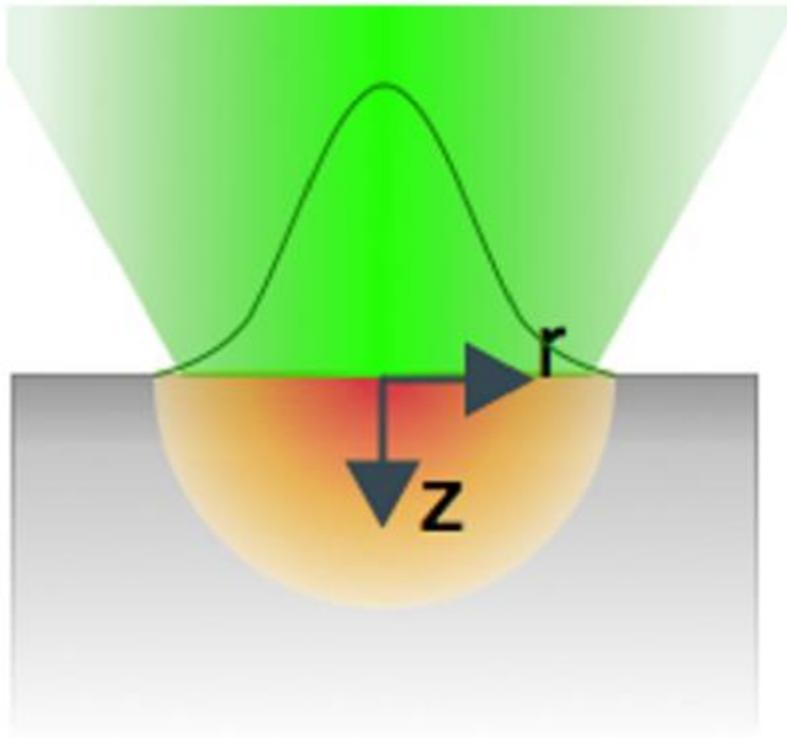
- Generally no, but it is best practice to run calibration

What is the recommended temperature rise for SSTR?

- ~5-10 K, but should be based on SNR
- With longer averaging times, smaller  $\Delta T$  (~1 K) can work

What can you do with SSTR?

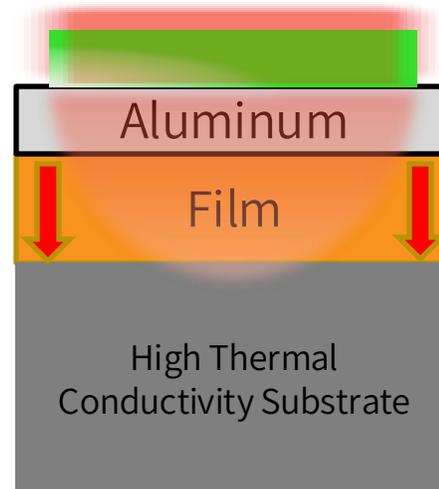
## Cross-plane, In-plane and sub-surface capabilities



For bulk materials, SSTR is sensitive to

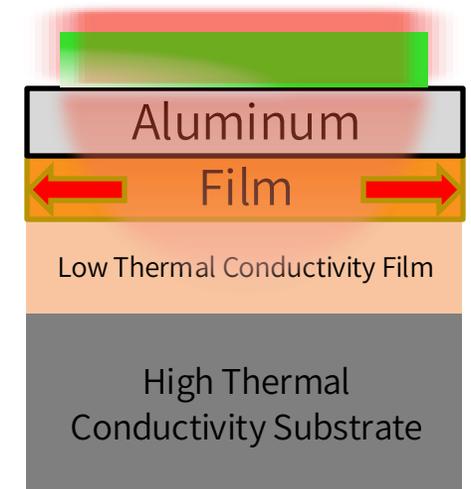
$$\kappa = \sqrt{\kappa_r \kappa_z}$$

### Cross-plane Measurement



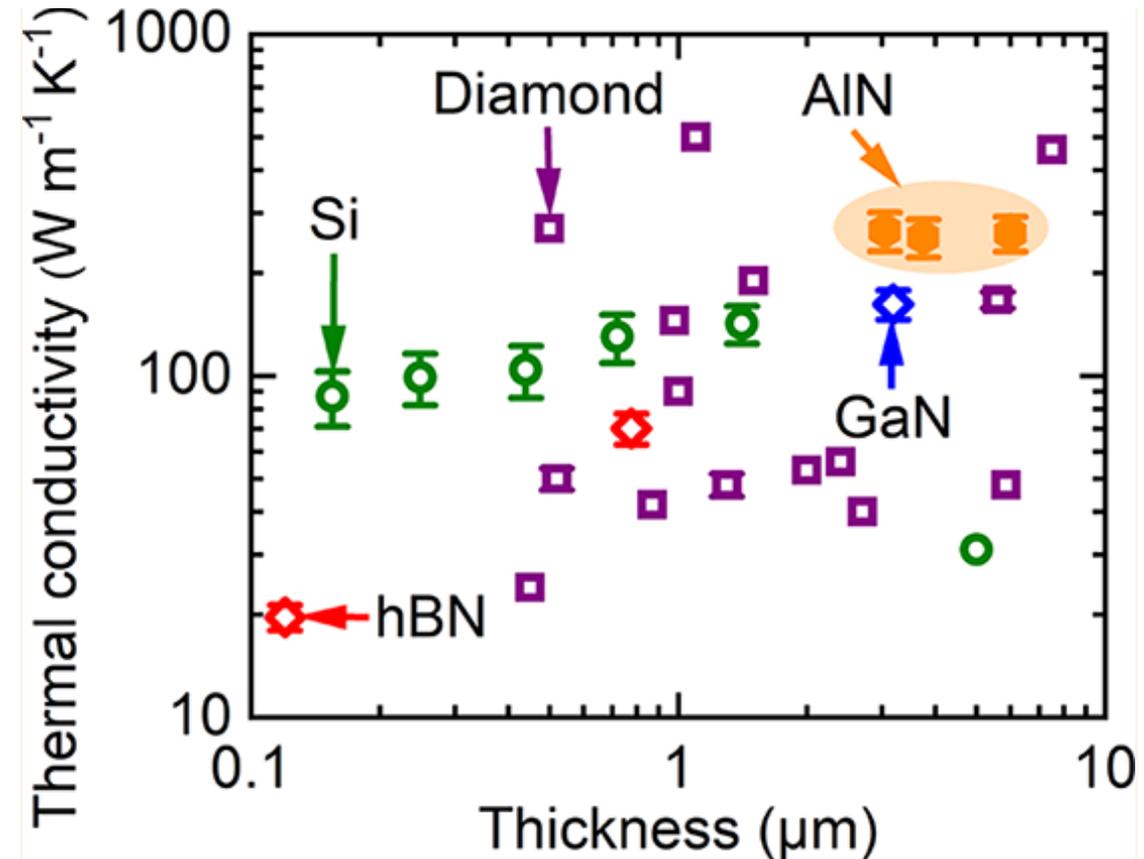
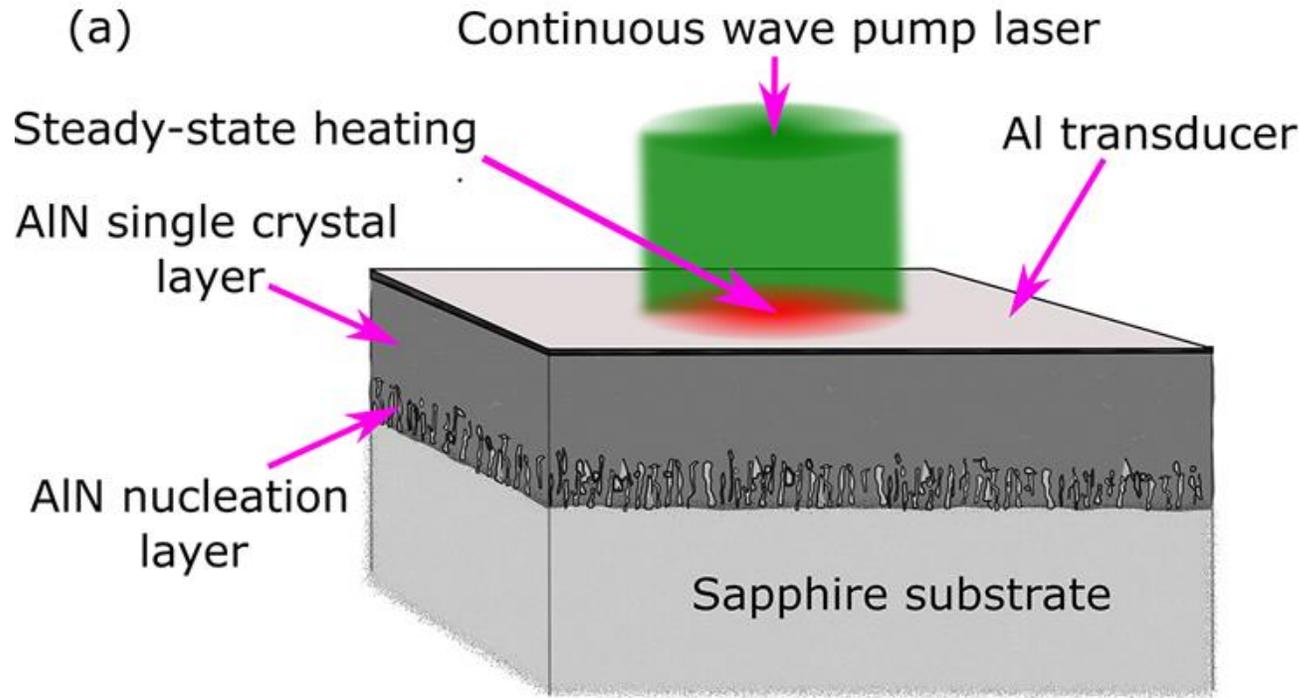
- Primary heat flow into substrate (cross-plane)
- Substrate is a heat sink
- Cross-plane case most valid for insulating films

### In-plane Measurement



- Primary heat flow is in-plane
- In-plane dominant for conductive films on insulating substrates/films
- Path of least resistance is in-plane

In-plane thermal conductivity of thin films  
e.g., anisotropy effects in AlN thin films

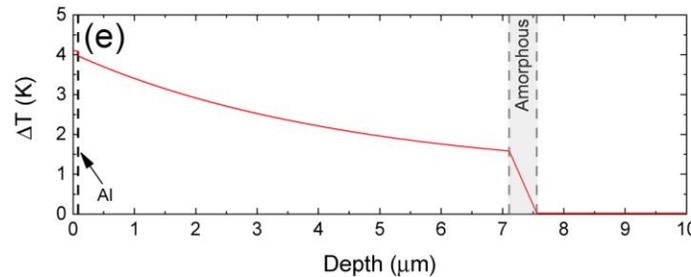
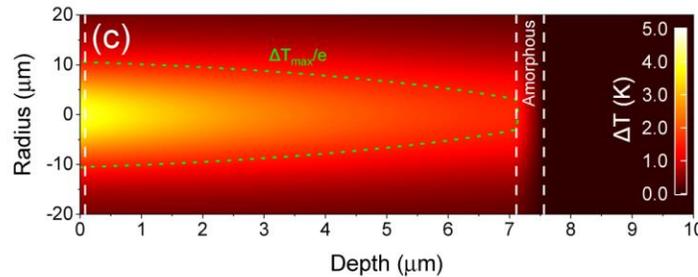


## Sub-surface defect detection

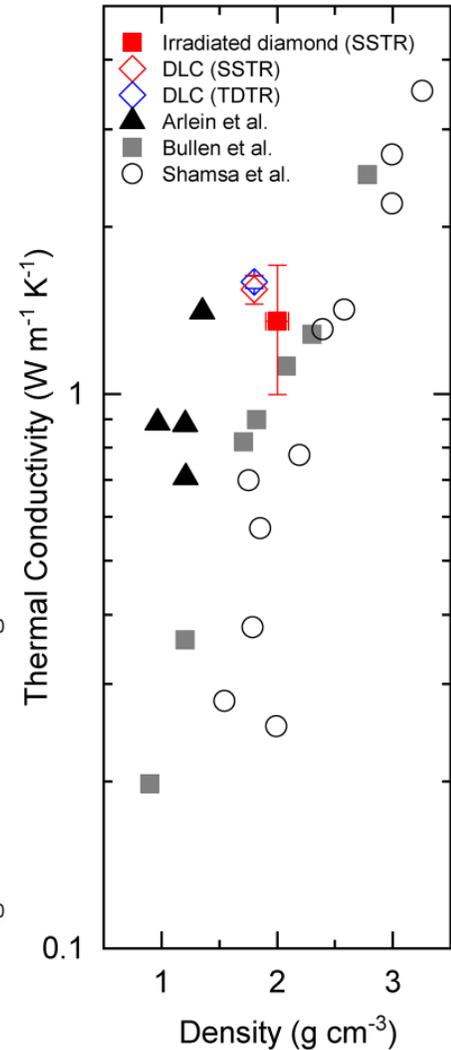
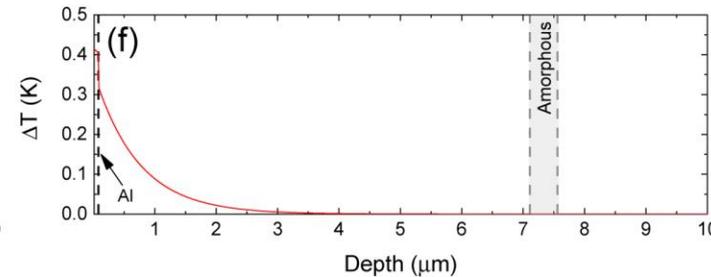
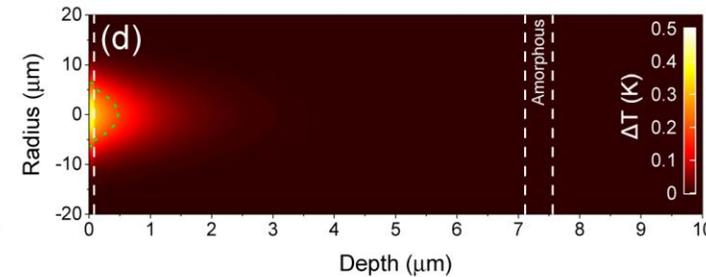
e.g., measure thermal conductivity of thin region with point defects 7  $\mu\text{m}$  under diamond surface



SSTR can measure at variable depths under the surface controlled by the laser spot size

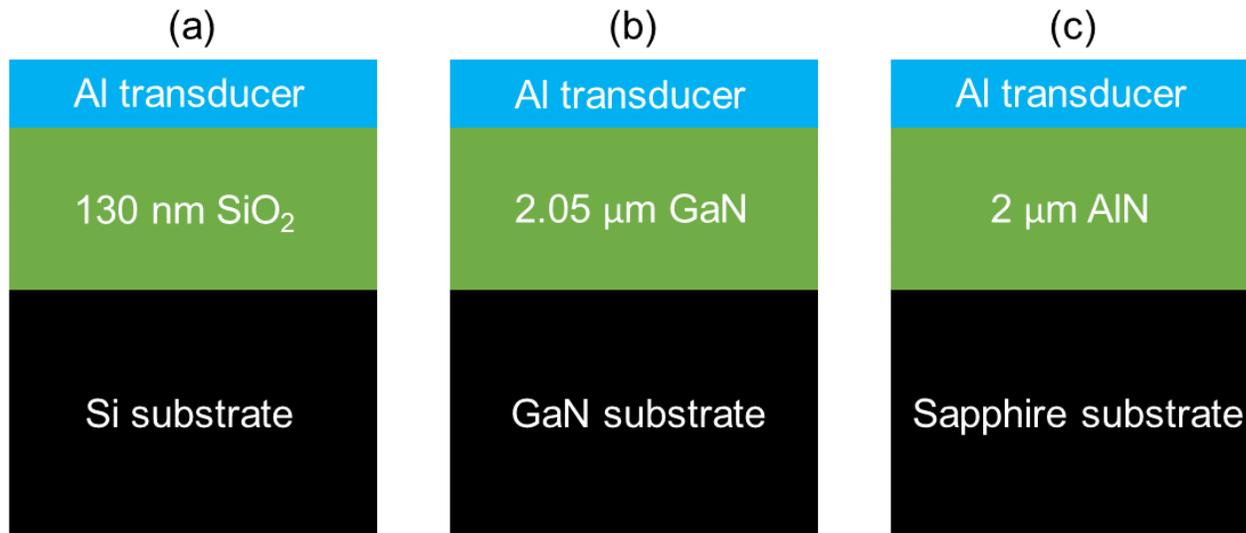


TDTR/FDTR restricted to  $\sim 1 \mu\text{m}$  beneath surface in diamond



## Sub-surface interfaces and heat sinks

e.g., measure thermal conductivity of buried interfaces, sub-mounts & substrates under GaN and AlN thin films



- Variable spot size allows measurement of multiple properties
- Measurement of layer-by-layer thermal conductivity in material stack/composite

Substrates	Thermal conductivity (W m <sup>-1</sup> K <sup>-1</sup> )		
	spot size 10 μm	spot size 20 μm	literature
Si	141 ± 27	140 ± 18	140 <sup>30</sup>
GaN	194 ± 27	185 ± 16	195 <sup>41</sup>
Sapphire	35.1 ± 5.9	34.5 ± 4.2	35 <sup>42</sup>

# Thank You!



BASIC RESEARCH | RESEARCH DIRECTORATE  
OFFICE OF THE UNDER SECRETARY OF DEFENSE FOR RESEARCH & ENGINEERING



Contact Information:  
Jeff Braun  
VP of Strategy & Programs  
[Jeff@LaserThermal.com](mailto:Jeff@LaserThermal.com)

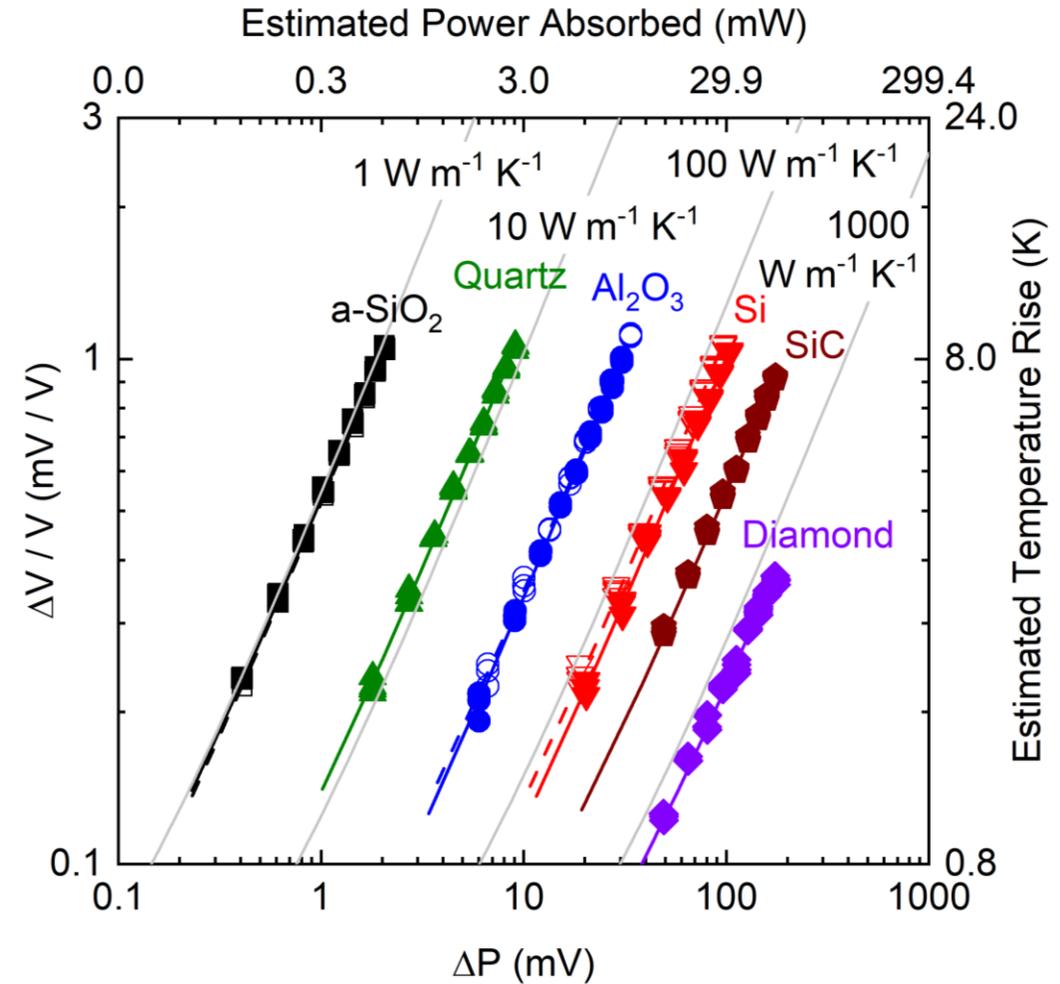
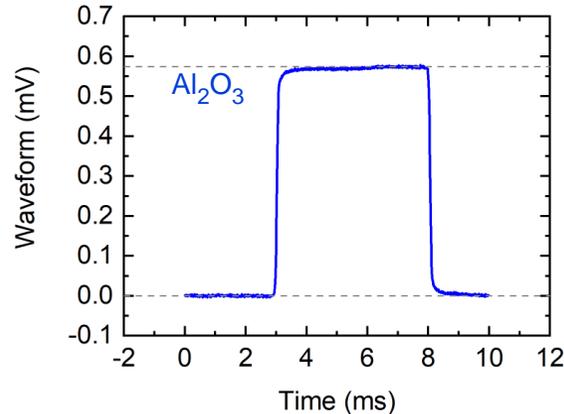
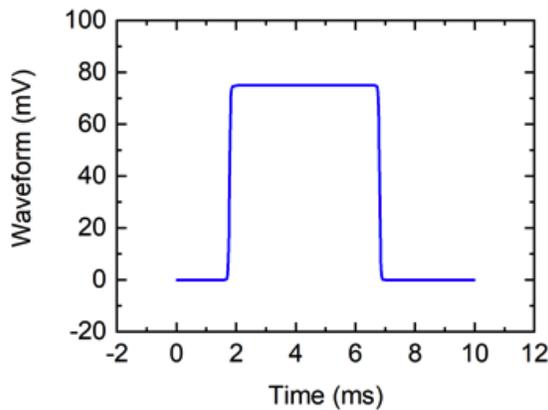
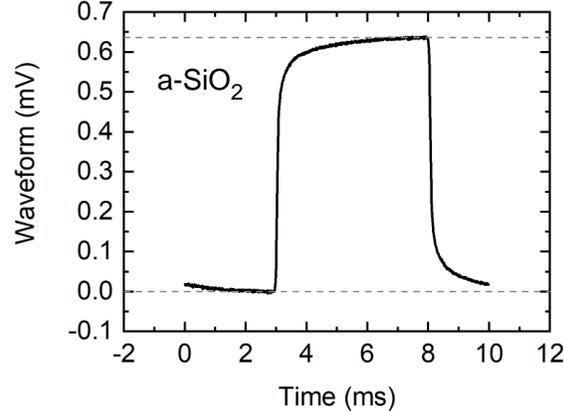
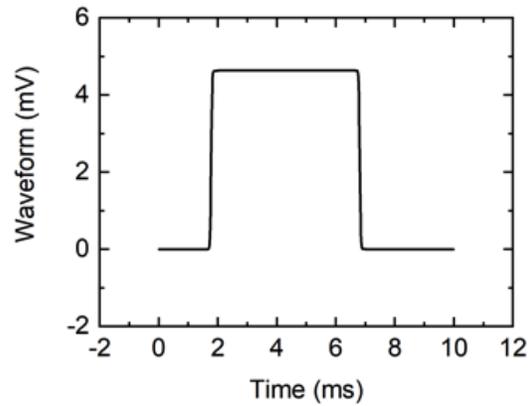


## Periodic Waveform Analyzer with Boxcar Averager

## Lock-in Amplifier

Pump Waveform

Temperature Response

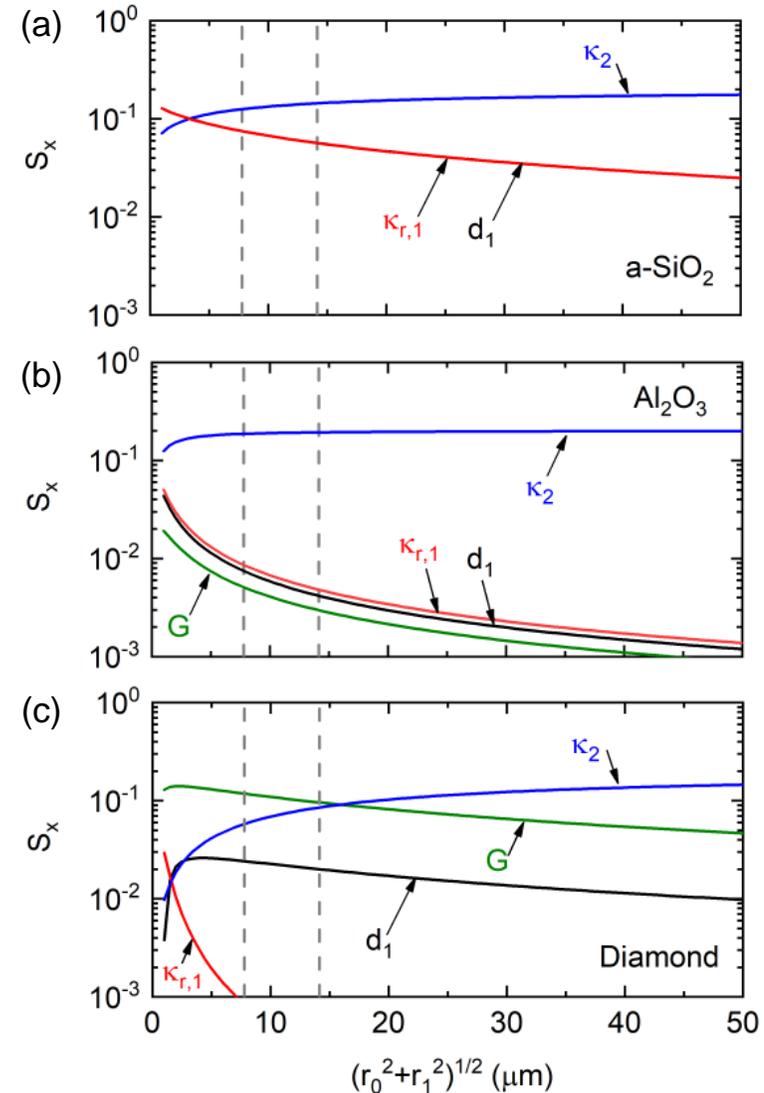


Sensitivity to parameter is defined by change in temperature response to  $\pm 10\%$  change in parameter magnitude

$$S_x = \frac{|\Delta T_{1.1x}(r_{01}) - \Delta T_{0.9x}(r_{01})|}{\Delta T_x(r_{01})}$$

$S_x$  is defined as a function of effective pump/probe radius

Changing  $r_{01}$  allows us to change sensitivity to various parameters of interest



# Sensitivity to thin films

